



TSMC N65 PDK usage guide:

An introduction on the usage of TSMC process design kits (PDK)

PDK Version: v1.0a Feb .07

TSMCN90RF PDK Usage Guide



Introduction:

- This document describes the TSMC process design kits (PDK) parameterized cell (Pcell) software, which provides a graphical user interface that lets user create parameterized cells for placement in design layout.
- It is assumed that the user is familiar with the development and design of integrated circuits and with the cadence Virtuoso Layout Editor.
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Overview:

■ The Symbol Display Information.

This section describes the symbol display information include four terminal NMOS symble, four terminal PMOS symbol, three terminal NMOS symbol, three terminal PMOS symbol, three terminal npn BJT symbol, three terminal pnp BJT symbol, two terminal diode symbol, two terminal resister symbol and two terminal varactor symbol.

Device Table

This section show the total device in this PDK. The user can check the page number in the device table to find out the CDF parameter and Pcell function.

- MOS Parameterized Cell Function Introduction
- BJT Parameterized Cell Function Introduction
- Diode Parameterized Cell Function Introduction
- Resistance Parameterized Cell Function Introduction
- Inductor Parameterized Cell Function Introduction
- Varactor Parameterized Cell Function Introduction
- Capacitor Parameterized Cell Function Introduction
- CDF Parameter Description
- Appendix

Appendix A – Abutment Fast link

Appendix B – Stretch Handles Fast link

Appendix C – The three terminal MOS substrate pin Fast link

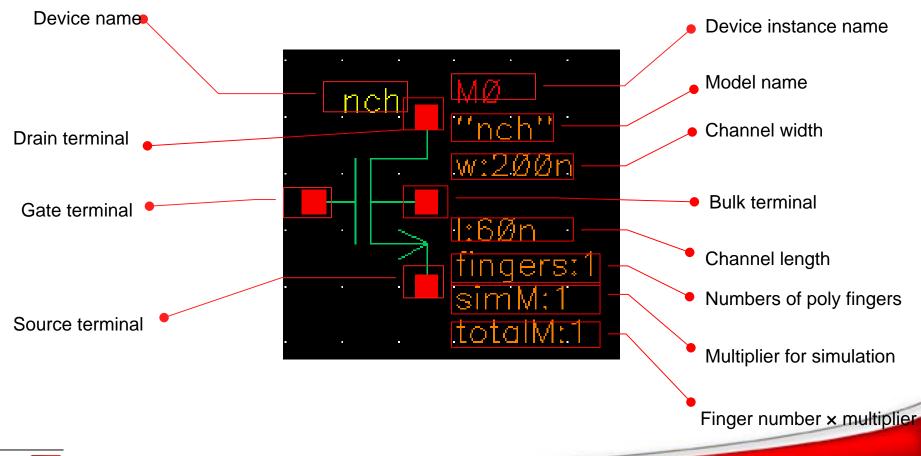
Appendix D – TSMC Utility Fast link

Appendix E – AS AD PS PD NRS NRD methodology Fast line

Appendix F – SA SB methodology Fast link

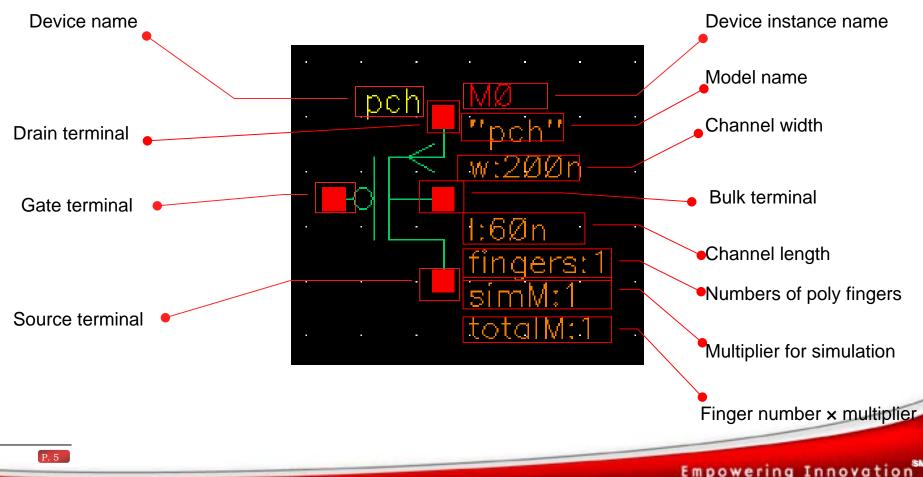


- The Symbol Display Information:
 - The following figure shows the symbol for a four terminal NMOS:



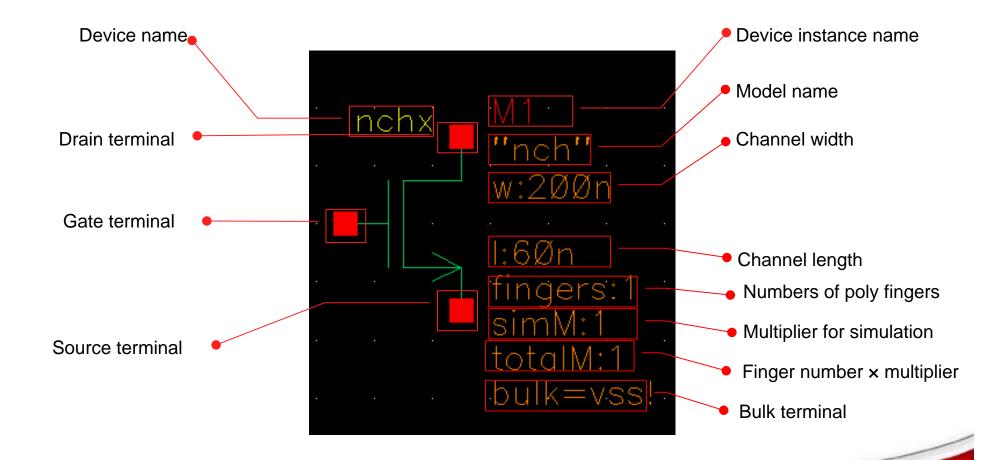


- **The Symbol Display Information:**
 - The following figure shows the symbol for a four terminal PMOS:



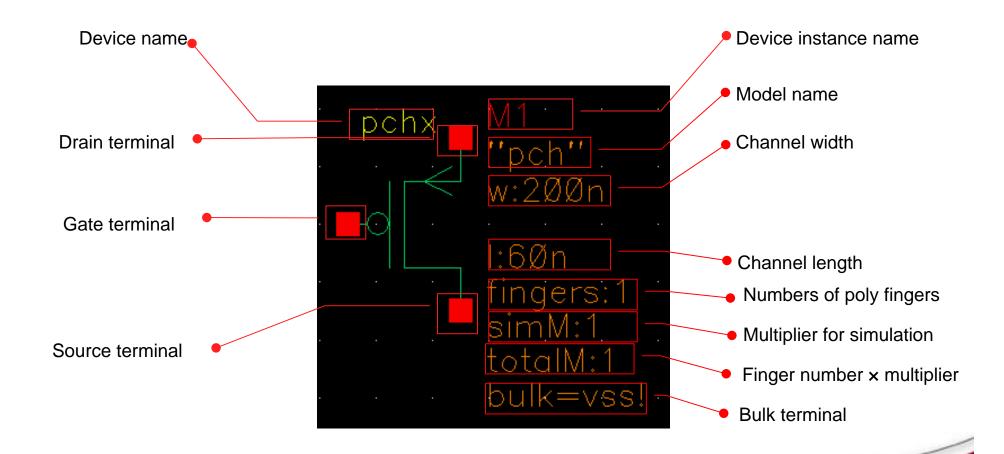


- The Symbol Display Information:
 - The following figure shows the symbol for a three terminal NMOS:



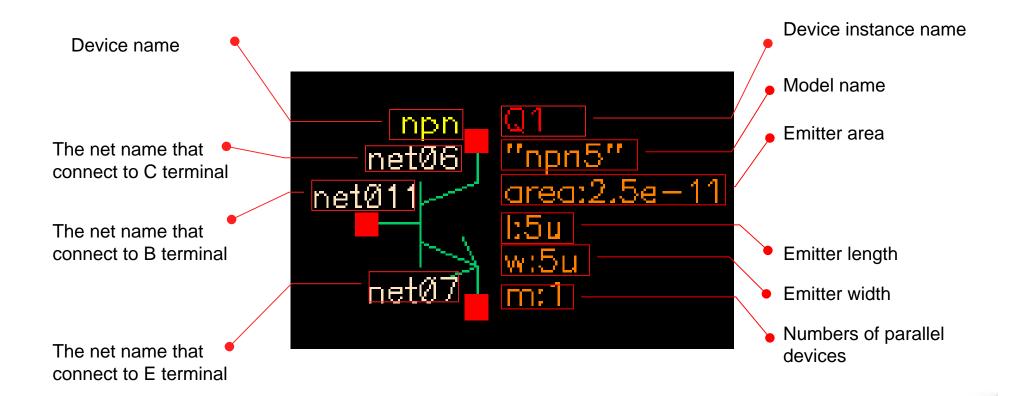


- The Symbol Display Information:
 - The following figure shows the symbol for a three terminal PMOS:



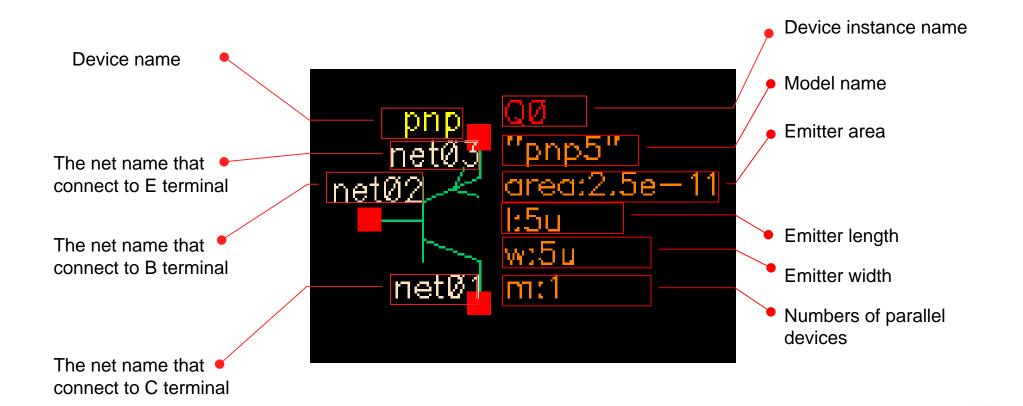


- The Symbol Display Information:
 - The following figure shows the symbol for a three terminal npn BJT:



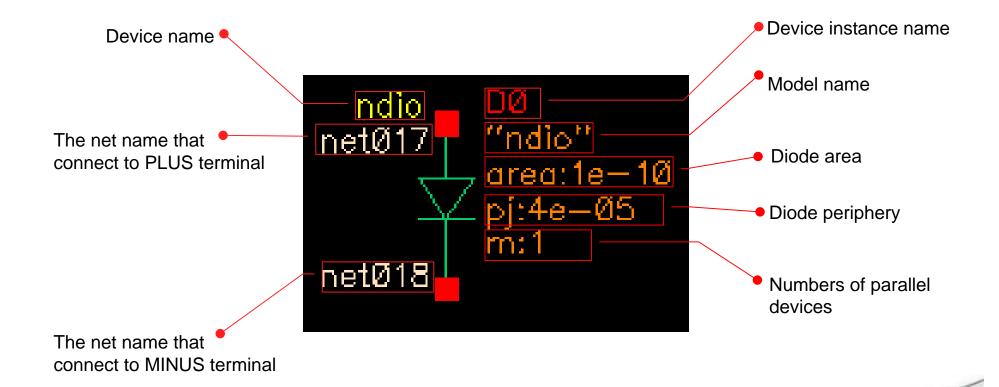


- The Symbol Display Information:
 - The following figure shows the symbol for a three terminal pnp BJT:



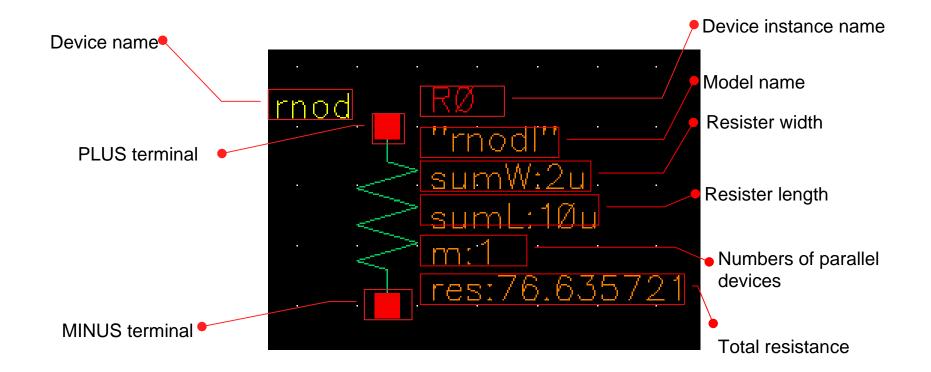


- The Symbol Display Information:
 - The following figure shows the symbol for a two terminal diode:



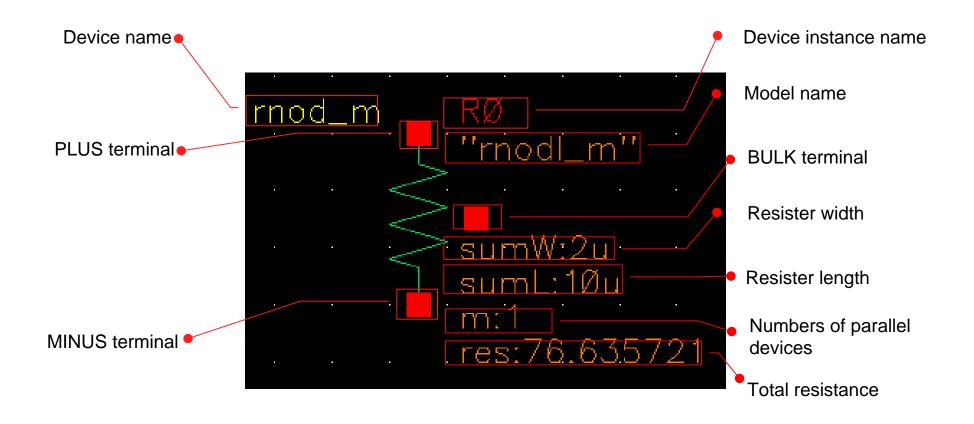


- The Symbol Display Information:
 - The following figure shows the symbol for a two terminal resister:



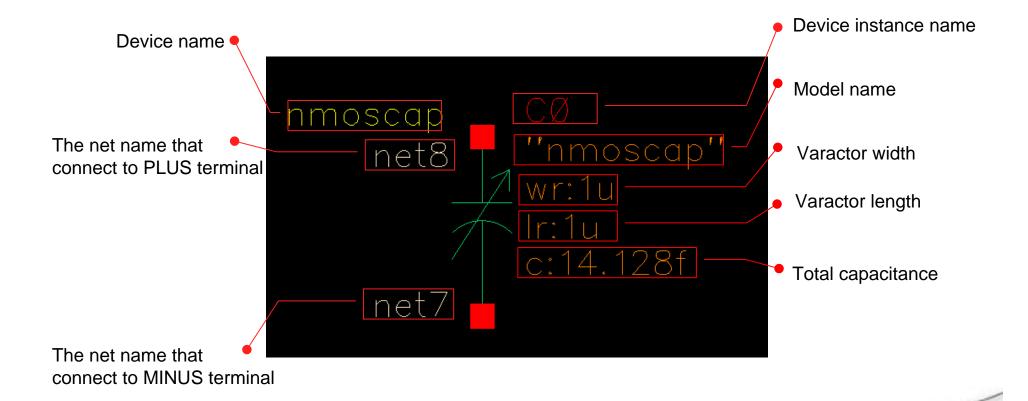


- The Symbol Display Information:
 - The following figure shows the symbol for a three terminal resister:



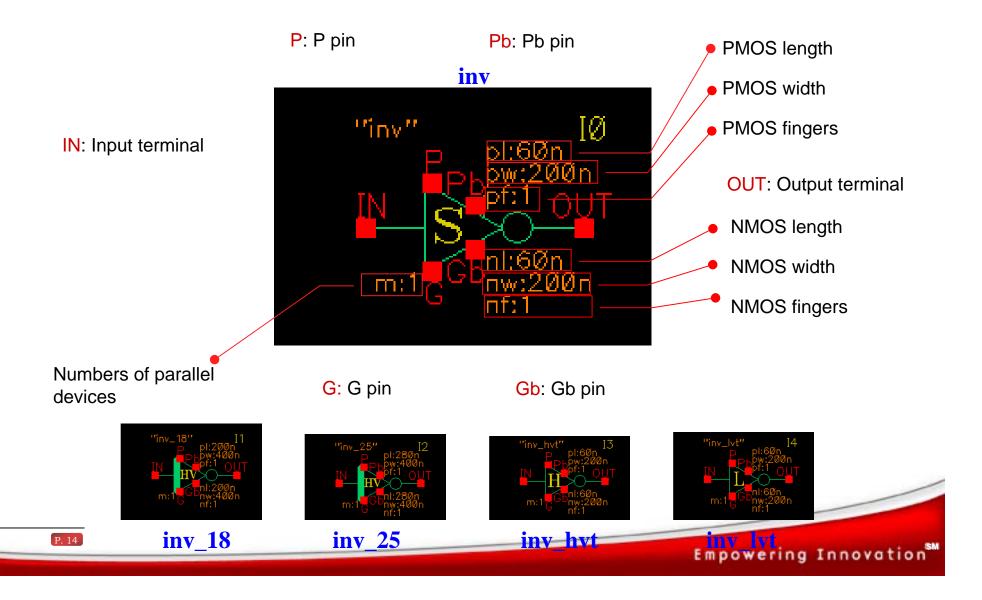


- The Symbol Display Information:
 - The following figure shows the symbol for a two terminal varactor:



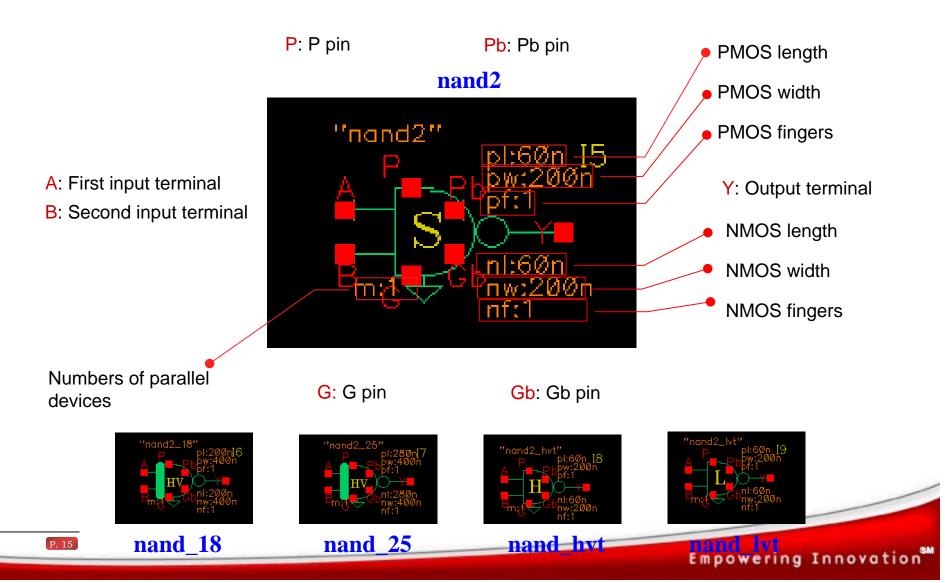


- The Symbol Display Information:
 - The following figure shows the symbol for a Inverter gate :





- The Symbol Display Information:
 - The following figure shows the symbol for a nand-2T gate :





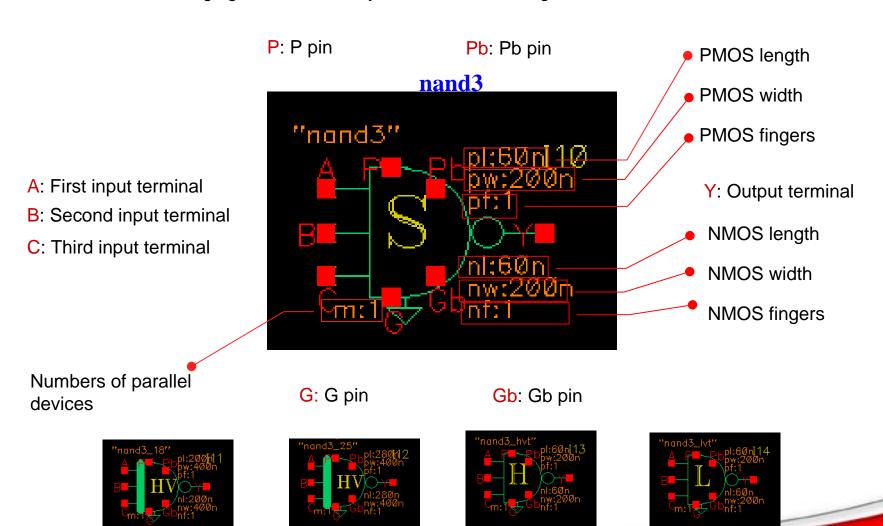
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- The Symbol Display Information:
 - The following figure shows the symbol for a nand-3T gate :

nand3_25

nand3_18

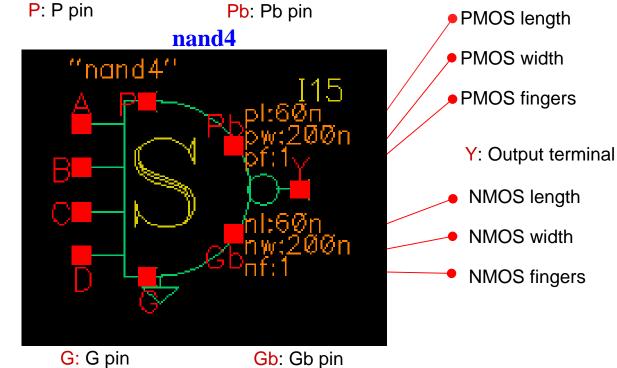
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nand3 by



- The Symbol Display Information:
 - The following figure shows the symbol for a nand-4T gate :





A: First input terminal

B: Second input terminal

C: Third input terminal

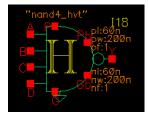
D: Fourth input terminal

nand4_18

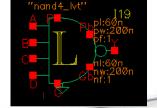
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nand4_25



nand4_byt

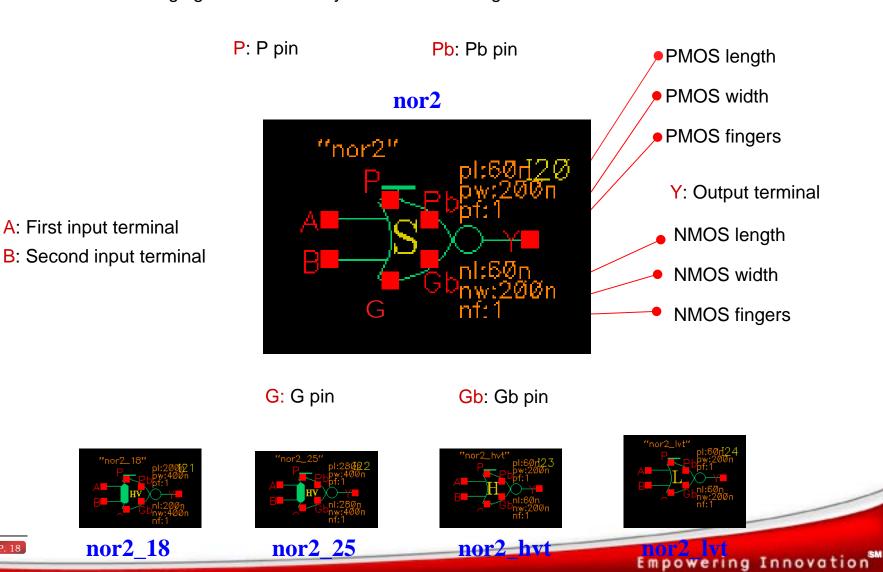




The Symbol Display Information:

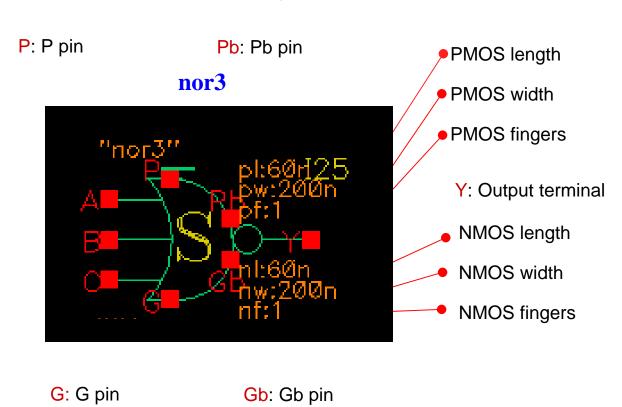
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The following figure shows the symbol for a nor-2T gate:





- The Symbol Display Information:
 - The following figure shows the symbol for a nor-3T gate :



A: First input terminal

B: Second input terminal

C: Third input terminal

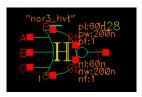


nor3_18

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nor3_25



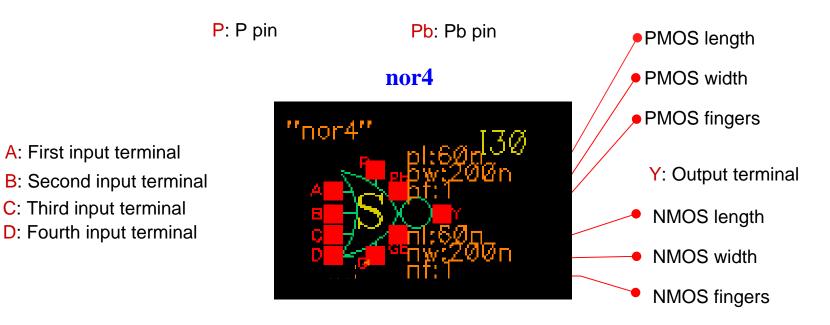
nor3 hyt







- The Symbol Display Information:
 - The following figure shows the symbol for a nor-4T gate :



G: G pin

Gb: Gb pin

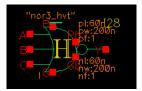


nor4_18

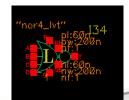
P. 20



nor4_25



nor4 hy

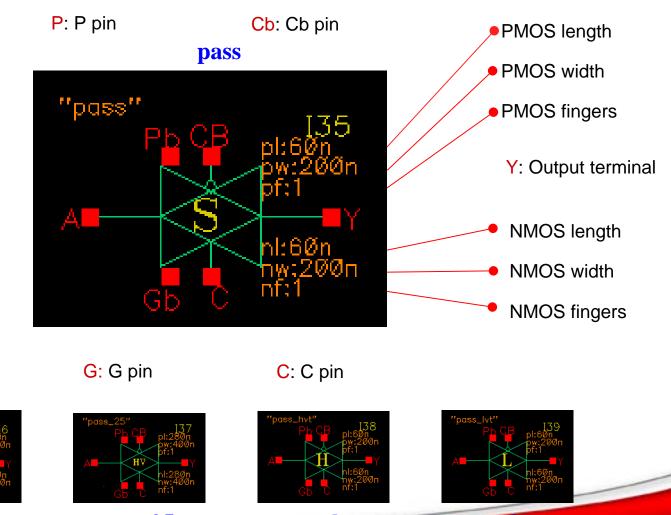






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- The Symbol Display Information:
 - The following figure shows the symbol for a pass gate :



"pass_18"

Pb CB pt: 2800

A: First input terminal

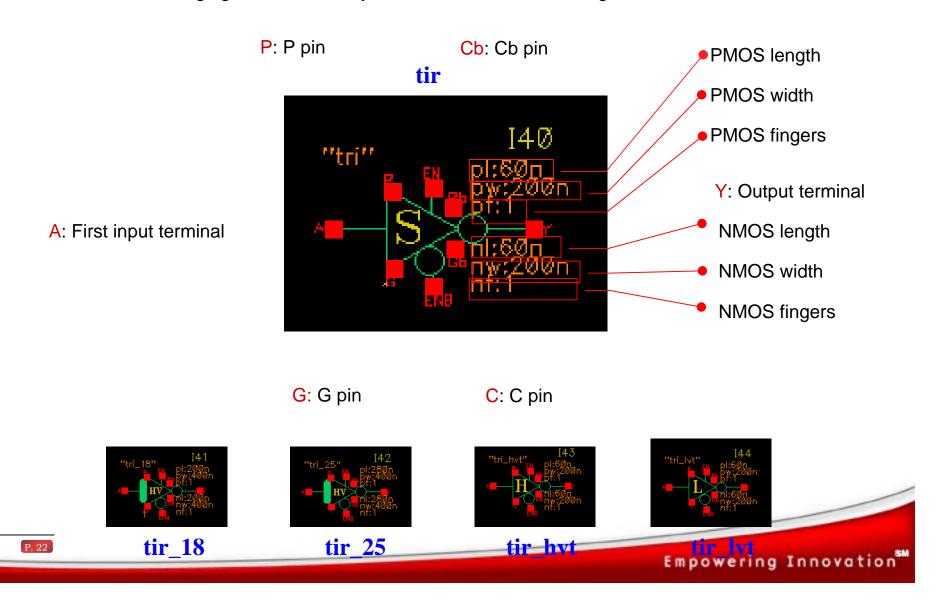
pass_18

pass_25

pass byt



- The Symbol Display Information:
 - The following figure shows the symbol for a Tri state inverter gate :





Device Table:

The devices in this PDK are list as below table:

Categaries	Device
MOS	nch, nch_dnw, nch_18, nch_18_dnw, nch_25, nch_25_dnw, nch33, nch33_dnw, nch_hvt, nch_hvt_dnw, nch_lvt, nch_lvt_dnw,
	nch_mlvt, nch_mlvt_dnw, nch_na, nch_na25, nch_18x, nch_18_dnwx, nch_25_dnwx, nch_33_dnwx, nch_hvt_dnwx,
	nch_lvt_dnwx, nch_mlvt_dnwx, nch_dnwx, nch_nax, nch_na25x, pch, pch_18, pch_25, pch_33, pch_hvt, pch_lvt,
	pch_mlvt, pch_18x, pch_25x, pch_33x, pch_hvtx, pch_lvtx, pch_mlvtx, pchx, nch_25x, nch_33x
MOS_MAC	pch_25_mac, pch_25_macx, pch_33_mac, pch_33_macx, pch_hvt_mac, pch_hvt_macx, pch_lvt_mac, pch_lvt_macx, pch_lvt_ma
	pch_macx, pch_mlvt_mac, pch_mlvt_macx, nch_25_mac, nch_25_macx, nch_33_mac, nch_33_macx, nch_hvt_mac,
	nch_hvt_macx, nch_lvt_mac, nch_lvt_macx, nch_mac, nch_mlvt_mac, nch_mlvt_macx, nch_25_dnw_mac,
	nch_25_dnw_macx, nch_33_dnw_mac, nch_33_dnw_macx, nch_dnw_mac, nch_dnw_macx, nch_hvt_dnw_mac,
	nch_hvt_dnw_macx, nch_lvt_dnw_mac, nch_lvt_dnw_macx, nch_mlvt_dnw_mac, nch_mlvt_dnw_macx
	nch_18_mac, nch_18_macx, nch_18_dnw_mac, nch_18_macx, pch_18_mac, pch_18_macx
MOS_RF	nmos_rf, nmos_rf_25, nmos_rf_hvt, nmos_rf_lvt, nmos_rf_mlvt, nmos_rf_nodnw, nmos_rf_25_nodnw, nmos_rf_hvt_nodnw,
	nmos_lvt_nodnw, nmos_mlvt_nodnw, pmos_rf, pmos_rf_25, pmos_rf_hvt, pmos_rf_lvt, pmos_rf_mlvt, pmos_rf_nw,
	pmos_rf_25_nw, pmos_rf_hvt_nw, pmos_rf_lvt_nw,pmos_rf_mlvt_nw, nmos_rf_18, nmos_rf_18_nodnw, nmos_rf_33,
	nmos_rf_33_nodnw, pmos_rf_18, pmos_rf_18_nw, pmos_rf_33, pmos_rf_33_nw
BJT	pnp, pnp_mis, npn, npn_mis
Diode	ndio, ndio_18, ndio_25, ndio_33, ndio_hvt, ndio_lvt, ndio_mlvt, ndio_na, ndio_na25, nwdio, pwdnw, dnwpsub, dnwpsub,
	ndio_esd, pdio, pdio_18, pdio_25, pdio_33, pdio_hvt, pdio_lvt, pdio_mlvt
Resistor(1)	rm1, rm2, rm3, rm4, rm5, rm6, rm7, rm8, rm9
Resistor(2)	rnod_m, rnodwo,rnodwo_m, rnpoly, rnpoly_m, rnpolywo, rnploywo_m, rnwod, rnwod_m, rnwsti, rnwsti_m, rpod, rpod_m,
	rpod_m, rpodwo, rpodwo_m, rppoly, rppoly_m, rppoly_rf, rppolywo, rppolywo_m, rppolywo_rf

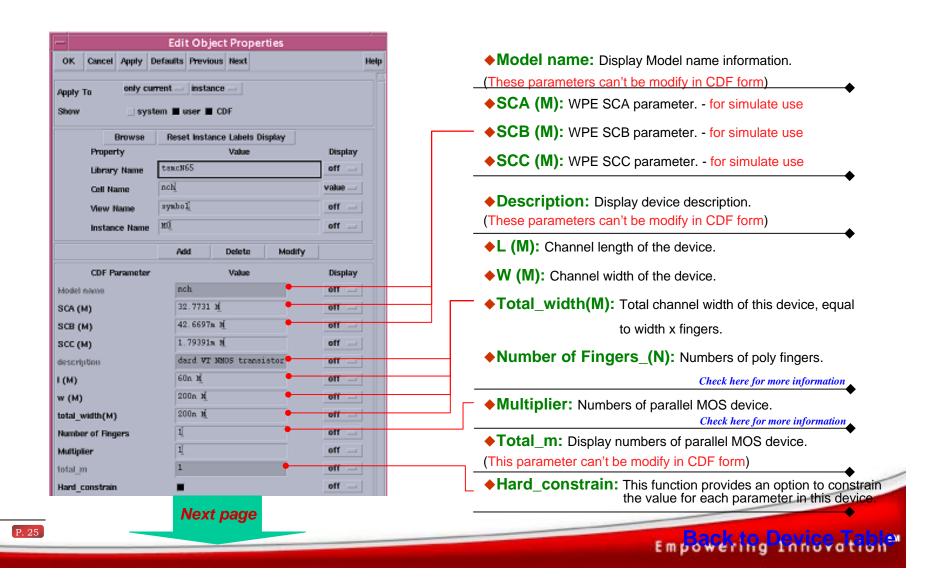


Device Table:

Capacitors	crtmom, crtmom_rf, mimcap, mimcap_um_rf, mimcap_woum_rf, crtmom_mx, mimcap_3t
Varactors	nmoscap, nmoscap_zf, moscap_rf25, moscap_rf2nw, moscap_rf25_nw,
	xjvar, xjvar_nw
Inductors	spiral_std_MU_Z, spiral_sym_MU_Z, spiral_sym_ct_MU_Z, spiral_std_MZA_A, spiral_sym_MZA_A,
	spiral_sym_ct_MZA_A,
Logic Gates	inv, inv_mac, inv_lvt, inv_lvt_mac, inv_hvt, inv_hvt_mac, inv_18, inv_18_mac, inv_25, inv_25_mac, inv_33, inv_33_mac, nand2,
	nand2_mac, nand2_lvt, nand2_lvt_mac, nand2_hvt, nand2_hvt_mac, nand2_18, nand2_18_mac, nand2_25, nand2_25_mac,
	nand2_33, nand2_33_mac, nand3_mac, nand3_lvt, nand3_lvt_mac,nand3_hvt, nand3_hvt_mac, nand3_18,
	nand3_18_mac, nand3_25, nand3_25_mac, nand3_33, nand3_33_mac, nand4,nand4_mac, nand4_lvt, nand4_lvt_mac,
	nand4_hvt, nand4_hvt_mac, nand4_18, nand4_18_mac, nand4_25, nand4_25_mac, nand4_33, nand4_33_mac, nor2,
	nor2_mac, nor3, nor3_mac, nor3_lvt, nor3_lvt_mac, nor3_hvt, nor3_hvt_mac, nor3_18, nor3_18_mac, nor3_25,
	nor3_25_mac, nar3_33, nar3_33_mac, nor4, nor4_mac, nor4_lvt, nor4_lvt_mac, nor2_lvt, nor2_lvt_mac, nor2_hvt,
	nor2_hvt_mac, nor2_18, nor2_18_mac, nor2_25, nor2_25_mac, nar2_33, nar2_33_mac, nor4_hvt, nor4_hvt_mac, nor4_18,
	nor4_18_mac, nor4_25, nor4_25_mac, nar4_33, nar4_33_mac, tri, tri_mac, tri_lvt, tri_lvt_mac, tri_hvt, tri_hvt_mac, tri_18,
	tri_18_mac, tri_25, tri_25_mac, tri_33, tri_33_mac, pass, pass_mac, pass_lvt, pass_lvt_mac, pass_hvt, pass_hvt_mac,
	pass_18, pass_18_mac, pass_25, pass_25_mac, pass_33, pass_33_mac



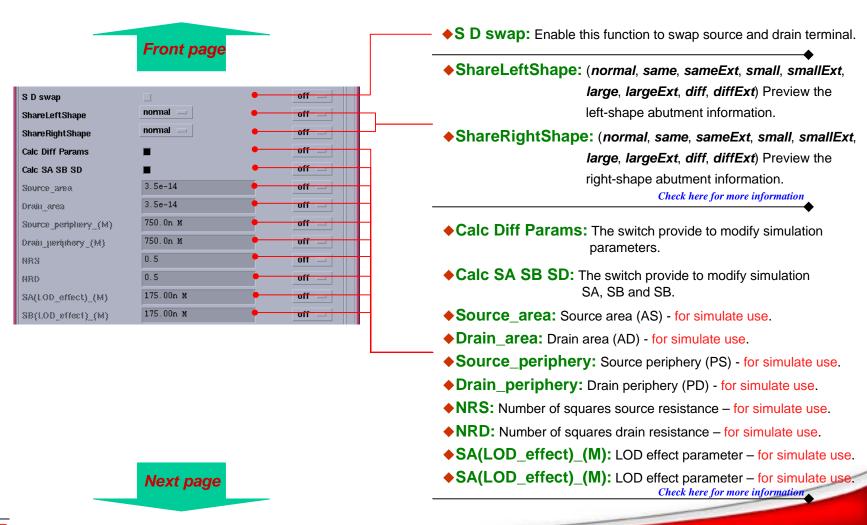
- MOS Parameterized Cell Function Introduction:
 - The schematic component description format (CDF) parameter in MOS are list as below:





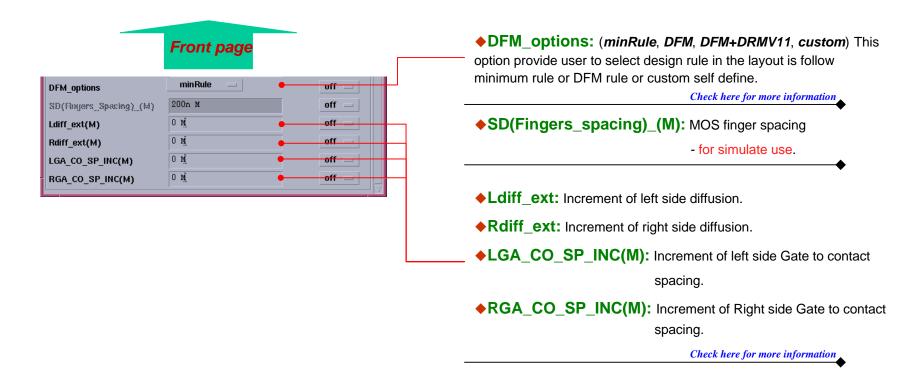
MOS Parameterized Cell Function Introduction:

■ The schematic component description format (CDF) parameter in MOS are list as below:





- MOS Parameterized Cell Function Introduction:
 - The schematic component description format (CDF) parameter in MOS are list as below:





MOS Parameterized Cell Function Introduction:

■ The **layout** component description format (CDF) parameter in MOS are list as below:

◆ Model name: Display Model name information.

◆SCA (M): WPE SCA parameter. - for simulate use

◆SCB (M): WPE SCB parameter. - for simulate use

◆SCC (M): WPE SCC parameter. - for simulate use

♦ Well_Proximity_Effect (M): Option for WEP - for simulate use (These are the same parameter that in schematic CDF form)

◆ **Description:** Display device description.

◆L (M): Channel length of the device.

◆W (M): Channel width of the device.

◆Total_width(M): Total channel width of this device, equal to width x fingers.

◆Number of Fingers_(N): Numbers of poly fingers.

◆Total_m: Display numbers of parallel MOS device.

◆ Hard constrain: This function provides an option to constrain

the value for each parameter in this device.

◆S D swap: Enable this function to swap source and drain terminal.

◆ShareLeftShape: Display the left-shape abutment information.

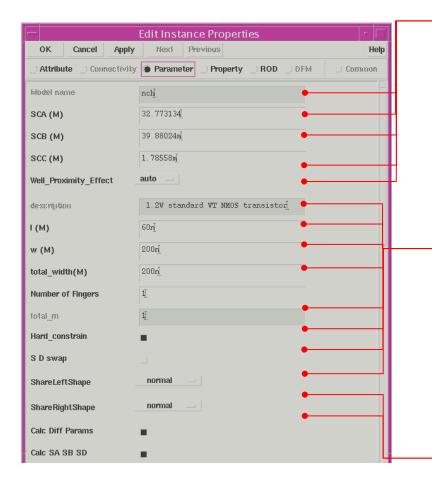
◆ShareRightShape:Display the right-shape abutment information.

(These are the same parameter that in schematic CDF form)

◆Calc Diff Params: The switch provide to modify simulation parameters.

◆ Calc SA SB SD: The switch provide to modify simulation SA, SB and SB.

These are the same parameter that in schematic CDF form



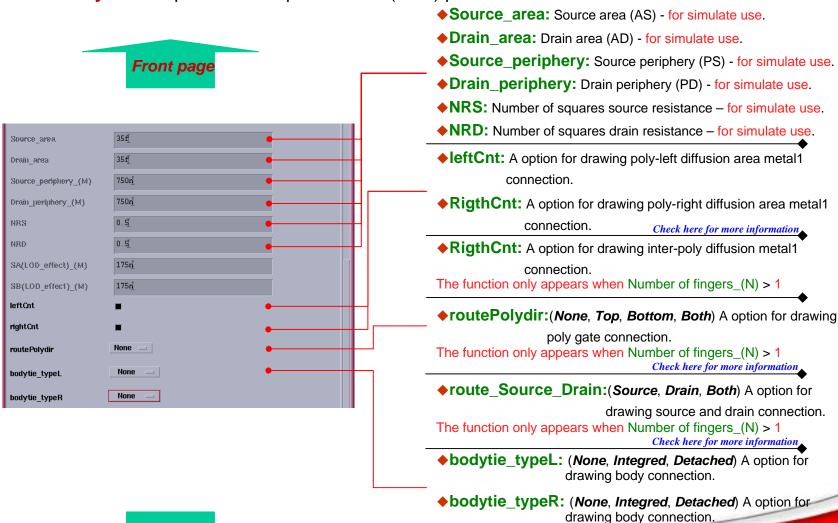


MOS Parameterized Cell Function Introduction:

Next page

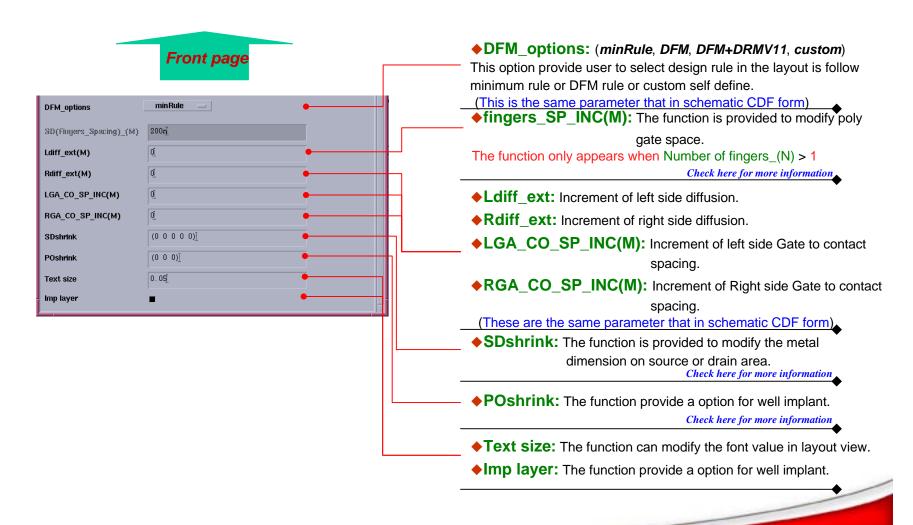
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The layout component description format (CDF) parameter in MOS are list as below:





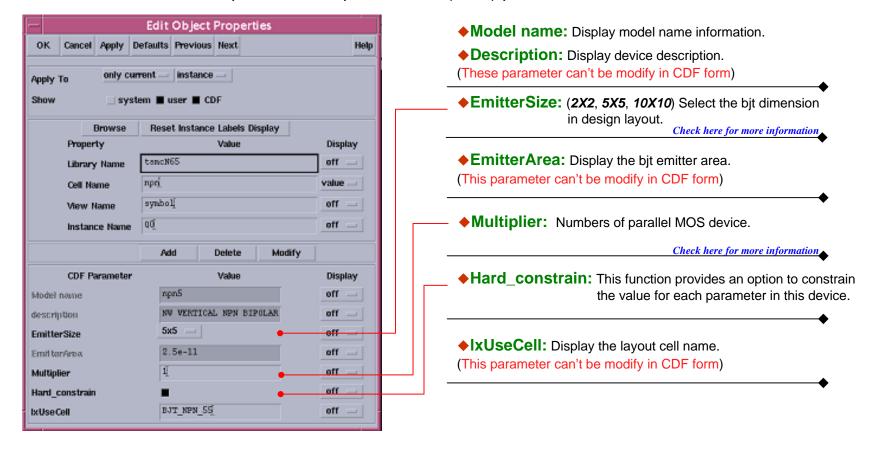
- MOS Parameterized Cell function Introduction:
 - The **layout** component description format (CDF) parameter in MOS are list as below:





BJT Parameterized Cell Function Introduction:

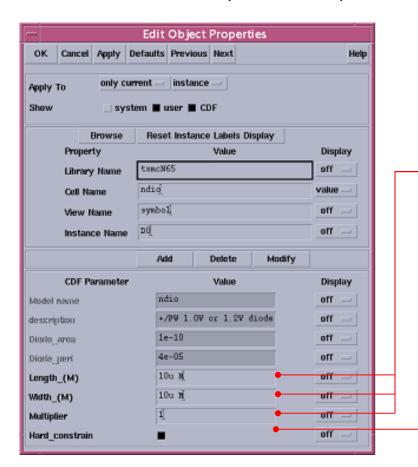
The schematic component description format (CDF) parameter in BJT are list as below:





Diode Parameterized Cell Function Introduction:

The schematic component description format (CDF) parameter in Diode are list as below:



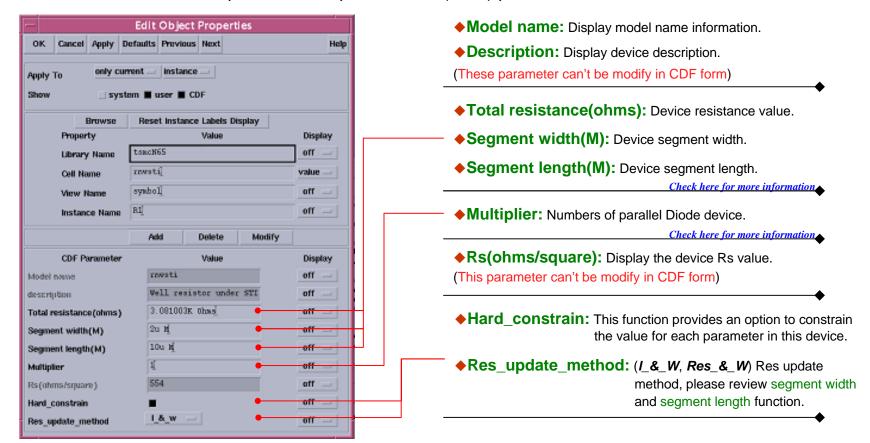
- Model name: Display model name information.
 Description: Display device description.
 Diode_area: Display the diode area.
 Diode peri: Display the diode periphery.
- (These parameter can't be modify in CDF form)
- ◆Length_(M): Junction length of the device.
- ◆Width_(M): Junction Width of the device.
- ◆ Multiplier: Numbers of parallel Diode device.

 Check here for more information
- +Hard_constrain: This function provides an option to constrain the value for each parameter in this device.

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- Resistance (1) Parameterized Cell Function Introduction:
 - The schematic component description format (CDF) parameter in resistance are list as below:





Em (Barrelo tog) Tennie a off

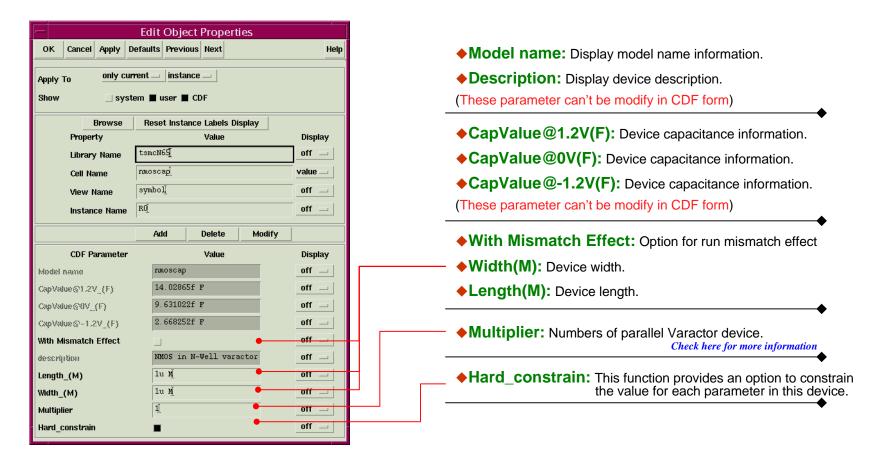
Resistance(2) Parameterized Cell Function Introduction:

The schematic component description format (CDF) parameter in resistance are list as below: ◆ Model name: Display model name information. **Edit Object Properties** OK Cancel Apply Defaults Previous Next Help ◆ **Description:** Display device description. ♦ With Mismatch Effect: Option for run mismatch effect only current instance Apply To Show ◆Total resistance(ohms): Device resistance value. Reset Instance Labels Display ◆Segment width(M): Device segment width. Display Property tsmcN65 Library Name ◆Segment length(M): Device segment length. rnod value Cell Name Check here for more information symbol off View Name ◆Total width(M): Display the device segment width. RŒ off Instance Name ◆Total length(M): Display the device segment length. Modify Add Delete ◆(These parameter can't be modify in CDF form) **CDF Parameter** Value Display rnodl off Model name ◆ Multiplier: Numbers of parallel Diode device. off Check here for more information With Mismatch Effect resistor with salicide off description ◆Rs(ohms/square): Display the device Rs value. 76.635721 Ohms Total resistance (ohms) (This parameter can't be modify in CDF form) 2u M off Total width(M) ◆ Resistor connection: Device resistance value. Segment width(M) 10u M Total length(M) off ◆ Number of segment: Device segment width. 10u M Segment length(M) ◆Segment spacing(M): Device segment length. off Check here for more information 15.52195217 off = Rs (ohms/square) ◆Cont columns: Device contact columns number. Resistor connection Series Parallel Check here for more information off Number of segments ◆ Hard_constrain: This function provides an option to constrain 180n M Segement spacing(M) the value for each parameter in this device. Cont columns ◆Res_update_method: (I_&_W, Res_&_W) Res update_ Hard constrain method, please review segre 1 & w Res update method



Varactor Parameterized Cell Function Introduction:

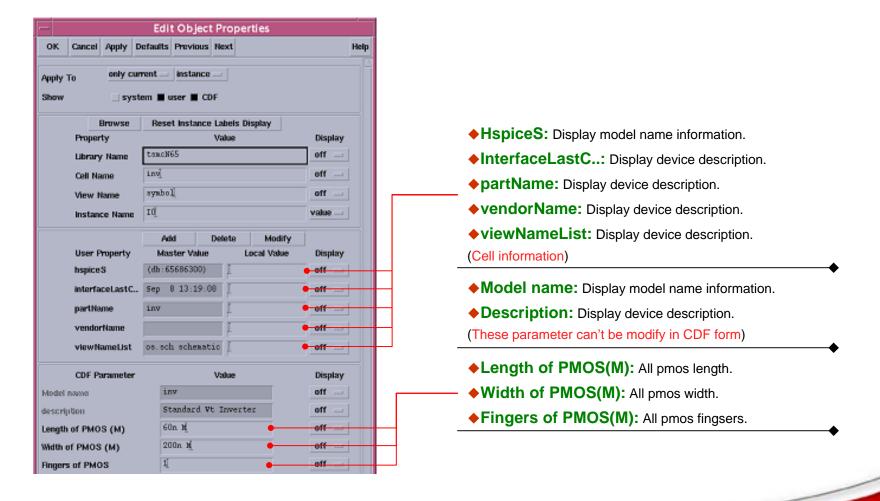
■ The schematic component description format (CDF) parameter in varactor are list as below:





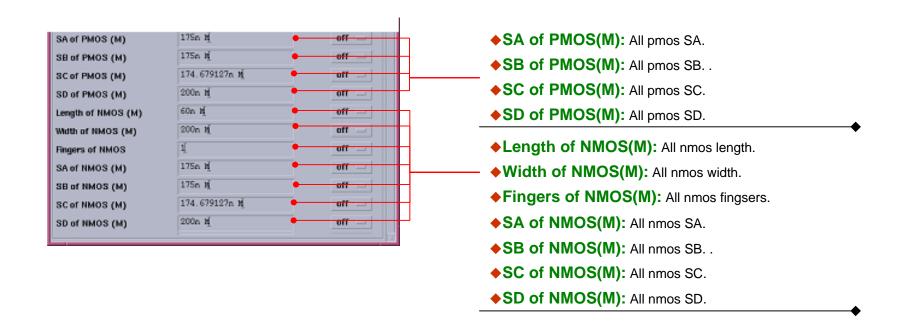
LogicGate Parameterized Cell Function Introduction:

The schematic component description format (CDF) parameter in inverter are list as below:





- LogicGate Parameterized Cell Function Introduction:
 - The schematic component description format (CDF) parameter in varactor are list as below:



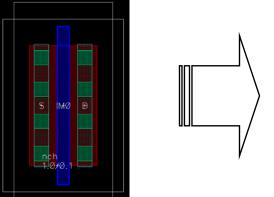


CDF Parameter Description

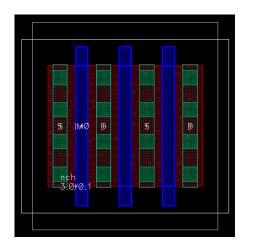


- The function of Number of Fingers_(N)
 - This parameter provide user to increment the poly finger numbers.

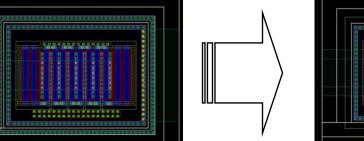
Number of Fingers_(N)=1



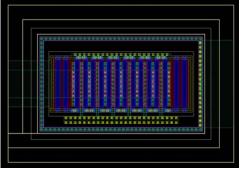
Number of Fingers_(N) =3



Number of Fingers_(N)=8



Number of Fingers_(N) =12

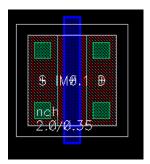


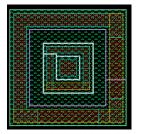


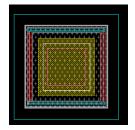
The function of Multiplier

■ This parameter provide user to increment the parallel device.

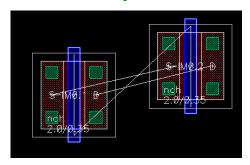
Multiplier = 1

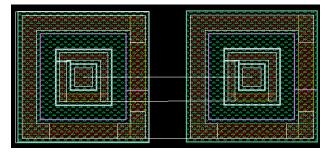


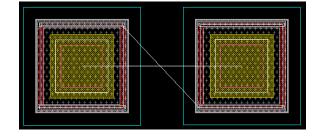




Multiplier = 2







Check here to back to MOS

Check here to back to BJT

Check here to back to Diode

Check here to back to Resistance(1)

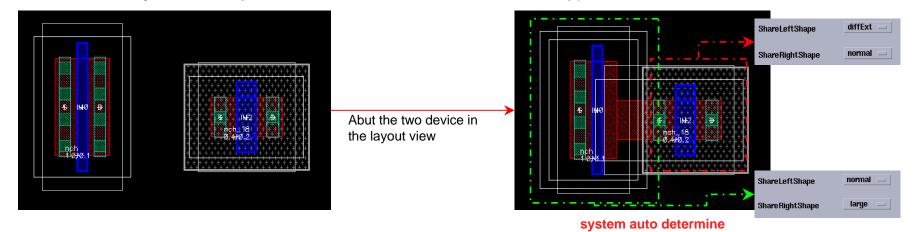
Check here to back to Resistance(2)

Check here to back to Varactor

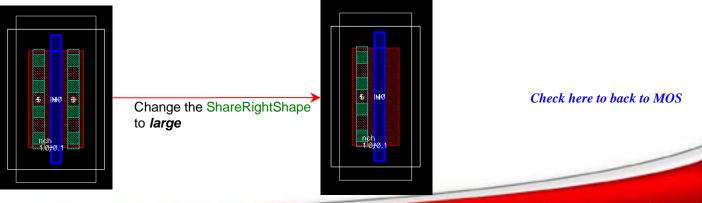


The function of ShareLeftShape and ShareRightShape

■ These functions provide user to preview the device difference before and after abutment. When the user abuts the devices in layout view, system will auto determine the abutment type of the both device. These two function can be selected to preview the layout but they can't be used to determine abutment type. Please check *Appendix A* for the details





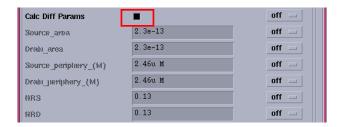




The function of Calc Diff Params and Calc SA SB SD

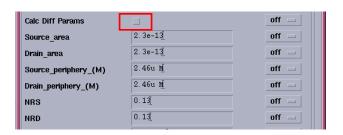
It's a switch for input simulation parameter that include area of source (AS), area of drain (AD), periphery of source (PS), periphery of drain (PD), number of squares source resistance (NRS), number of squares drain resistance (NRD) and LOD effect parameter- SA, SB and SD. Modify those parameters only influence simulation conditions, the design layout will not have any different.

Calc Diff Params is enable



Parameters can't be modify

Calc Diff Params is disable



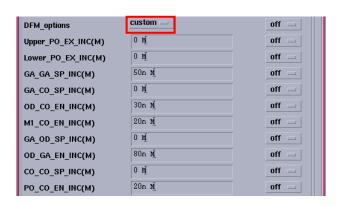
Parameters can be modify



The function of DFM_options

■ This option provides user to select design rule in the layout is follow minimum rule or DFM rule¹ or custom self define. When User selects the *custom* selection, the input spaces appear below the DFM_options. *DFM* option will check PO.EX.1, PO.EN.1.R, PO.EN.2.R and PO.EN.3.R rule.

DFM_options = custom



CDF parameter V.S Design Rule number comparison table

CDF Parameter	TSMC N65 Design Rule
Upper_PO_EX_INC(M)	PO.EX.1
Lower_PO_EX_INC(M)	PO.EX.1
GA_GA_SP_INC(M)	PO.S.11.R
GA_CO_SP_INC(M)	CO.EN.3.R
OD_CO_EN_INC(M)	CO.EN.1.R
M1_CO_EN_INC(M)	M1.EN.1.R
GA_OD_SP_INC(M)	PO.S.5.R
OD_GA_EN_INC(M)	PO.EX.2.R
CO_CO_SP_INC(M)	-
PO_CO_EN_INC(M)	CO.EN.3.R
NW_GA_SP_INC(M)	PO.EN.1.R
	PO.EN.3.R
OD2_GA_EN_INC(M)	PO.EN.2.R

Design rule document number:T-N65-CL-DR-001

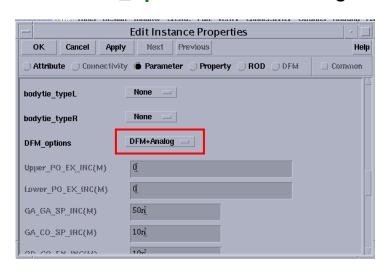
¹ Design For Manufacturing (DFM) rule is a recommendation rule that TSMC provide customer to minimized _ process variation and yield benefit. For the details, please review TSMC 65NM CMOS Design RULE.



The function of DFM_options

■ This option provides user to select design rule in the layout is follow minimum rule or DFM rule¹ or custom self define. When User selects the *custom* selection, the input spaces appear below the DFM_options. The *DFM+Analog* will check PO.EN.1m, PO.EN.2m, PO.EN.3m.

DFM_options = *DFM+Analog*



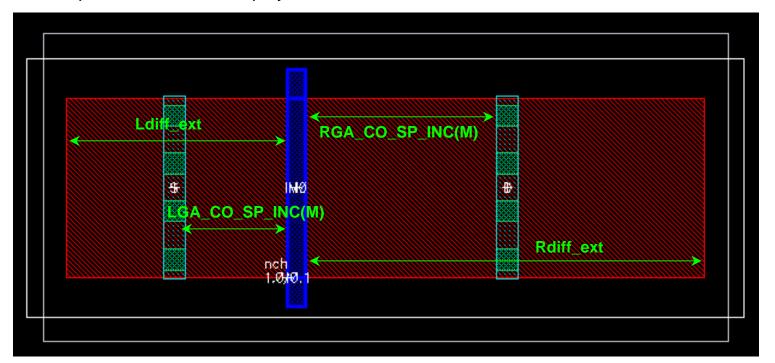
DFM+Analog option check the following rules:

PO.EN.1m >= 1.0um PO.EN.2m >= 2.0um PO.EN.3m >= 1.5um

¹ Design For Manufacturing (DFM) rule is a recommendation rule that TSMC provide customer to minimized process variation and yield benefit. For the details, please review TSMC 65NM CMOS Design RULE.



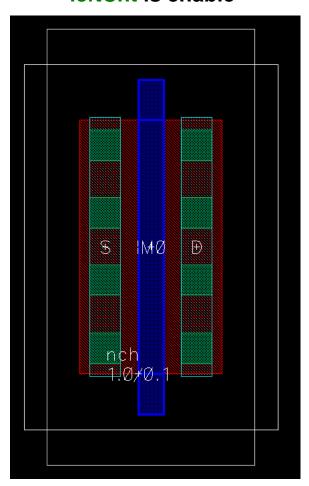
- The function of Ldiff_ext, Rdiff_ext, LGA_CO_SP_INC(M) and RGA_CO_SP_INC(M)
 - Those function provide user to increment the area of left and right diffusion and the space form contact to poly.



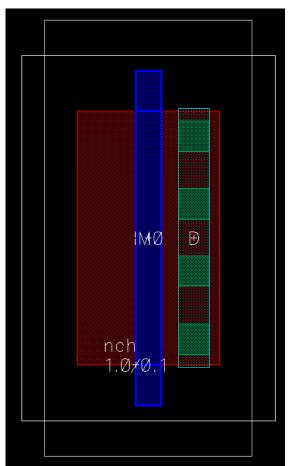


- The function of leftCnt, RightCnt
 - The function provide a option for drawing poly-left (right) diffusion area metal1 connect

leftCnt is enable

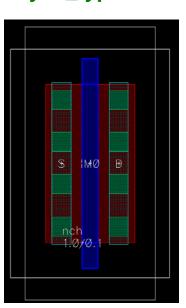


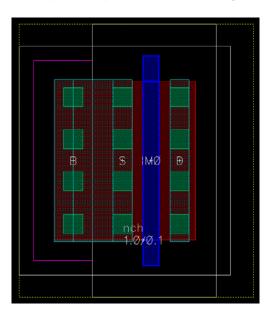
leftCnt is Disable



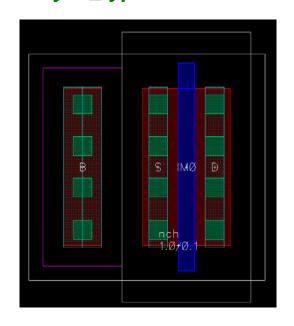


- The function of bodytie_typeL and bodytie_typeR
 - The function provide a option for drawing body connection at the device left (bodytie_typeL) or device right (bodytie_typeR).





bodytie_typeL is None bodytie_typeL is Integred bodytie_typeL is Detached







The function of SDshrink

■ The function is provided to modify the metal dimension on source or drain area. It's a list include five numbers. The first number is used to decide which metal user want to modify. The second number is used to shrink the dimension of the metal top. The third number is used to shrink the dimension of the metal bottom. The fourth number is used to extend the dimension of the metal left and right. The fifth number is used to increment the contact space in the metal. The number of these five numbers must be positive and the unit is micrometer.

(ABCDE)

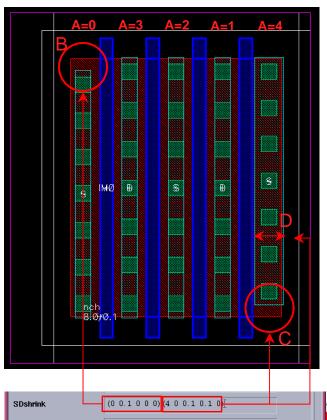
A:select metal

B:metal Top shrink

C:metal bottom shrink

D:metal side shrink

E:contact space increment





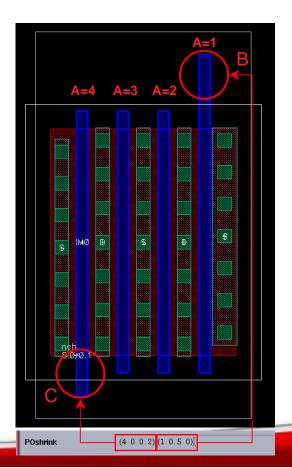


The function of POshrink

■ The function is provided to modify the poly gate dimension. It's a list include three numbers. The first number is used to decide which metal user want to modify. The second number is used to shrink the dimension of the poly gate top. The third number is used to shrink the dimension of the poly gate bottom. The number of these three numbers must be positive and the unit is micrometer.

(A B C)

A:select poly gate
B:poly gate top shrink
C:poly gate bottom shrink





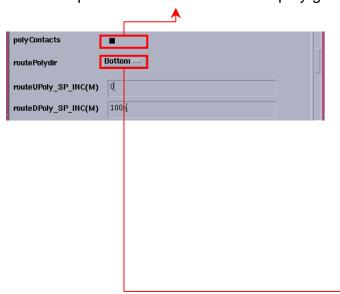


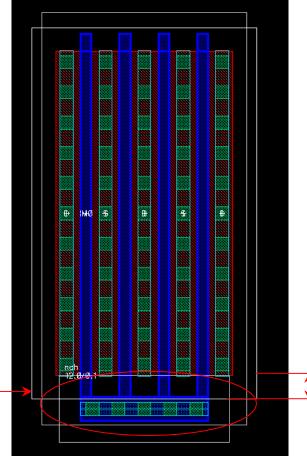
The function of routePolydir

■ The function is provided to drawing poly gate connection. The space of poly gate connection to the diffusion area can be modify by routeUPoly_SP_INC(M) and

routeDPoly_SP_INC(M) ².

The **poly Contacts** will appear when **routPolydir** doesn't None. It is an option to draw contact on the poly gate.





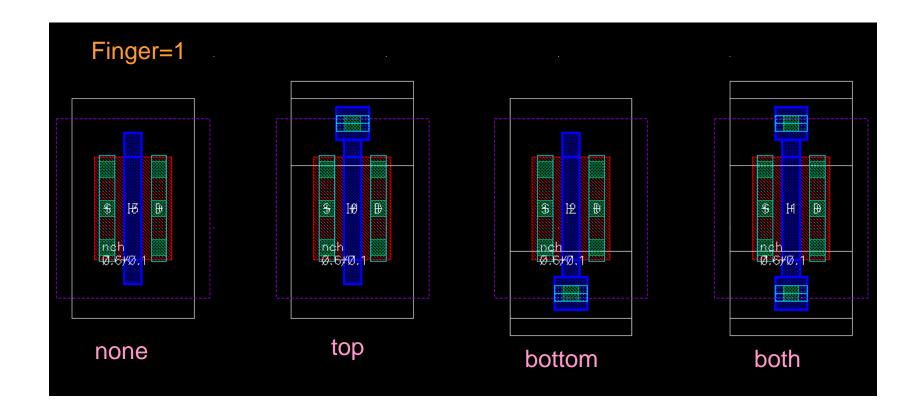
PO.S.6(design rule) + routeDPoly_SP_INC

²The routeUPoly_SP_INC(M) and routeDPoly_SP_INC(M) only appear when routePolydir doesn't **None.**

TSMCN65 PDK Usage Guide The function of routePolydir



- - The function is suggest to use in multi-finger. If customer use only one finger and turn on the routePolydir none/top/bottom/both direction. It will shows the following layout.

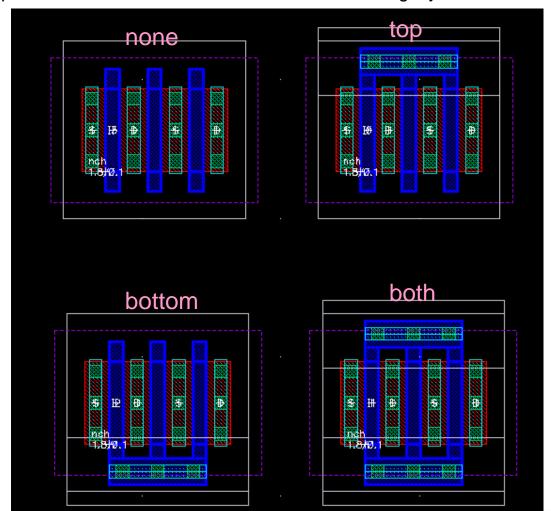


TSMCN65 PDK Usage Guide The function of routePolydir



- - Finger number=3. If customer use finger number=3 and turn on the routePolydir none/top/bottom/both direction. It will shows the following layout.

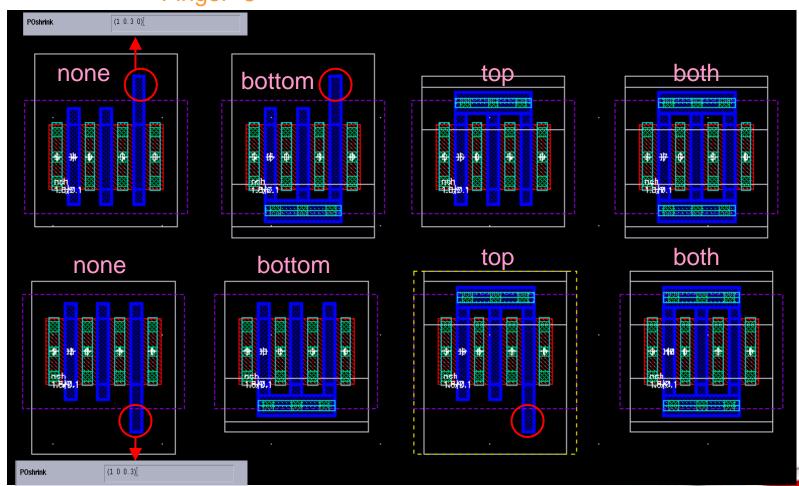
Finger=3



TSMCN65 PDK Usage Guide The function of routePolydir



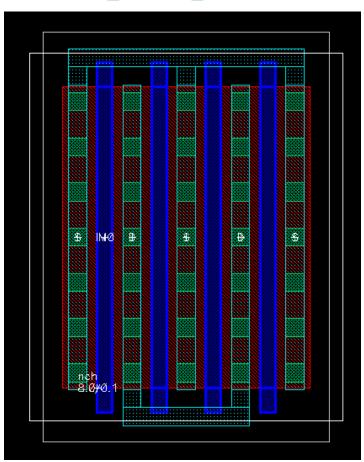
Finger number=3. Customer use finger number=3 and turn on the routePolydir none/top/bottom/both direction. At the same time customer uses Poshrink option as following: Finger=3





- The function of route_Source_Drain
 - The function is provided to drawing source and drain connection.

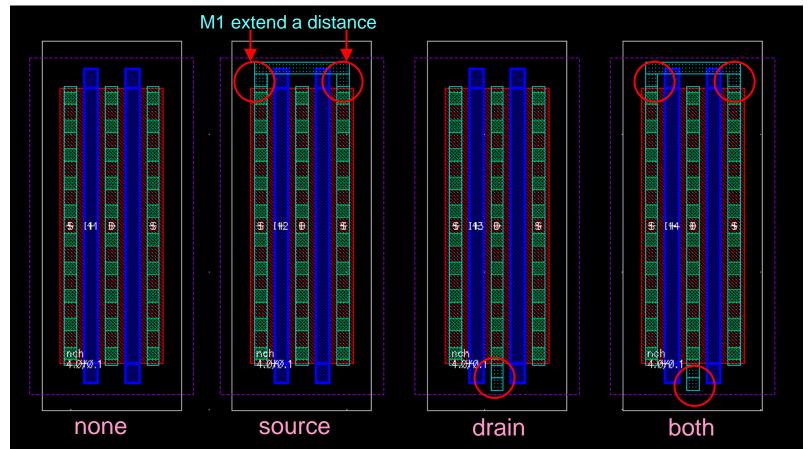






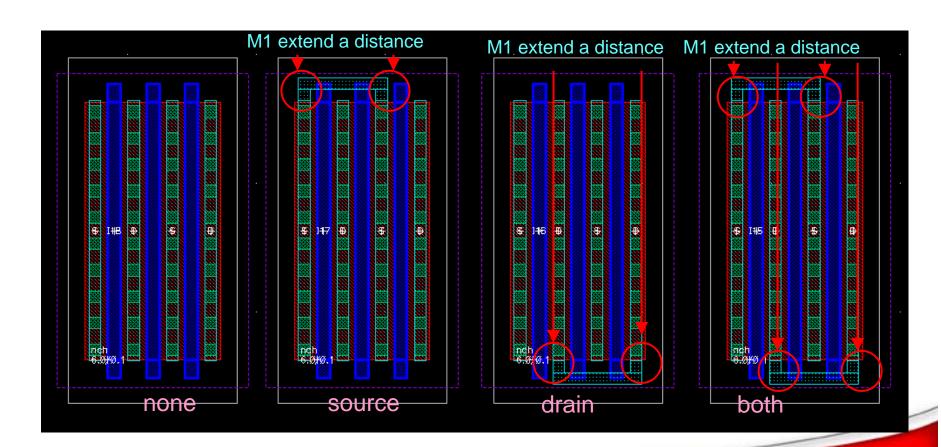


- The function of route_Source_Drain
 - The function is provided to drawing source and drain connection(it happens to nf >1). User need to pay attention for the following case Nf=2; it means the mos has two source and one drain. If you turn on this function your source-drain metal layer will extend a distance.



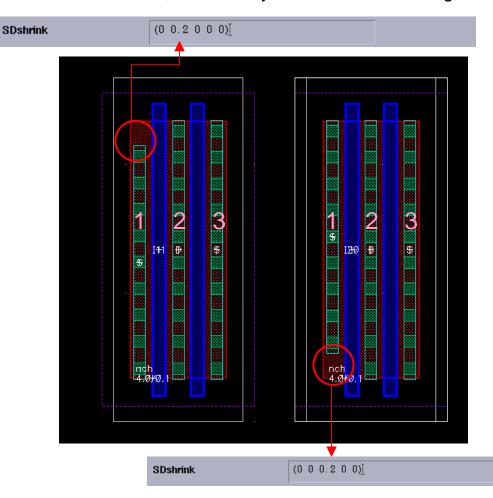


- The function of route_Source_Drain
 - The function is provided to drawing source and drain connection(it happens to nf >1). User need to pay attention for the following case Nf=3; it means the mos has two source and one drain. If you turn on this function your source-drain metal layer will extend a distance.



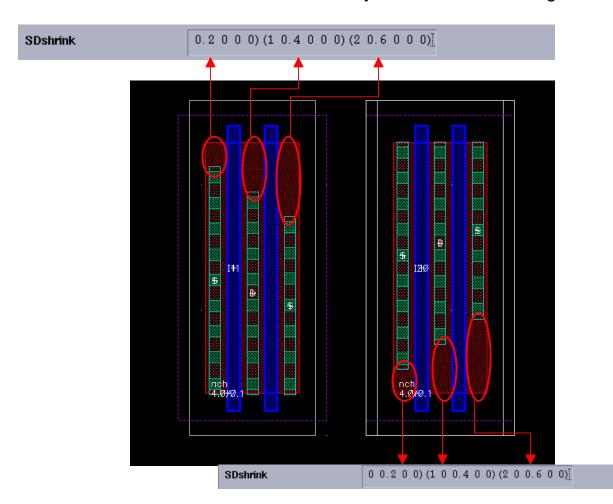


- The function of route_Source_Drain
 - The function is provided to drawing source and drain connection(it happens to nf >1). User set SD shrink function, the mos layout will shrink the length as following.



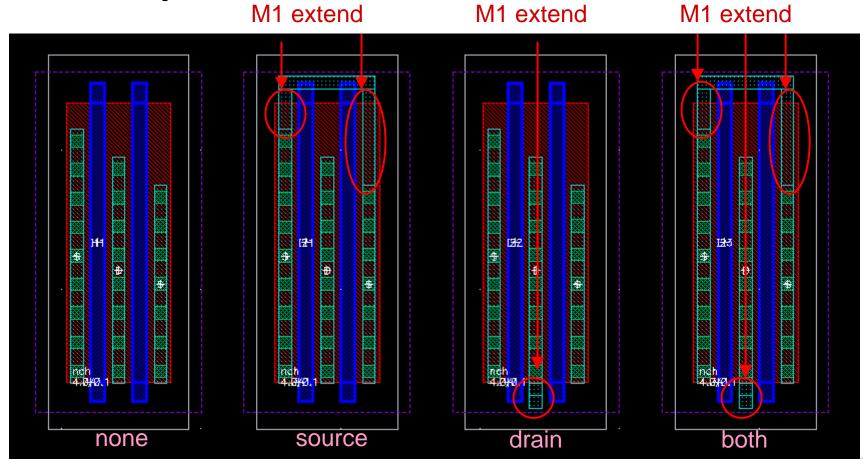


- The function of route_Source_Drain
 - The function is provided to drawing source and drain connection(it happens to nf >1). User set SD shrink function, the mos layout will shrink the length as following.



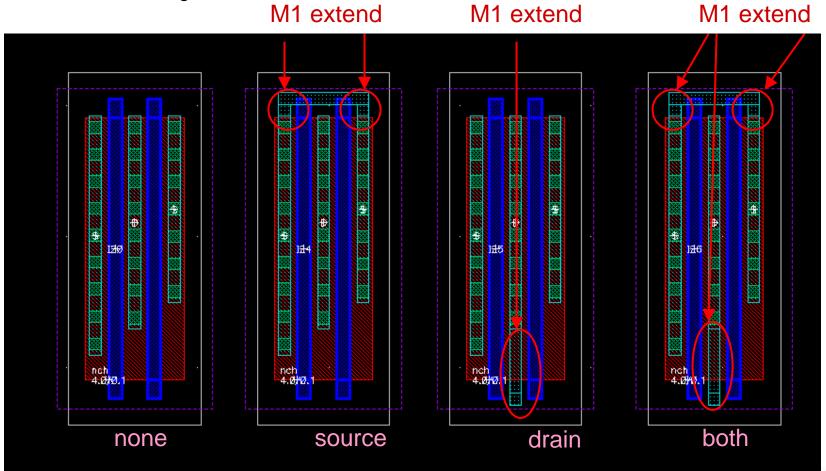


- The function of route_Source_Drain
 - The function is provided to drawing source and drain connection(it happens to nf >1). User set SD shrink function+route_source_drain, the mos layout will shrink the length as following.





- The function of route_Source_Drain
 - The function is provided to drawing source and drain connection(it happens to nf >1). User set SD shrink function+route_source_drain, the mos layout will shrink the length as following.





The function of route_Source_Drain

■ The function is provided to drawing source and drain connection(it happens to nf >1). User set SD shrink function+route_source_drain+routePolydir, the mos layout will shrink the length as following.Note with SD route, the poly will extend more length than none SD route.

routePolydir:NONE routePolydir:TOP



The function of route_Source_Drain

■ The function is provided to drawing source and drain connection(it happens to nf >1). User set SD shrink function+route_source_drain+routePolydir, the mos layout will shrink the length as following.Note with SD route, the poly will extend more length than none SD route.

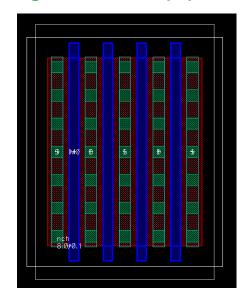
routePolydir:Bottom

routePolydir:Both

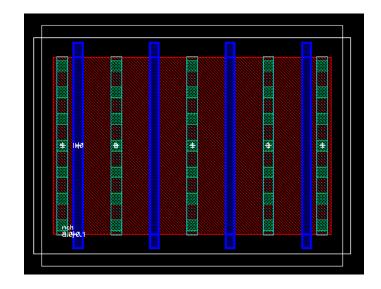


- The function of fingers_SP_INC(M)
 - The function provide user to modify poly gate space. Fingers_SP_INC(M) is a increase value, it's not a distance between poly gate.

$$fingers_SP_INC(M) = 0$$

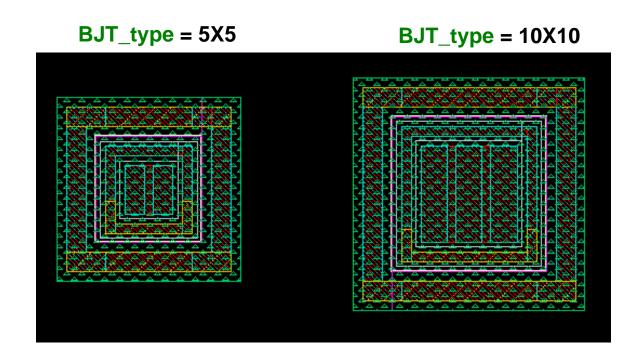


$$fingers_SP_INC(M) = 0.5$$





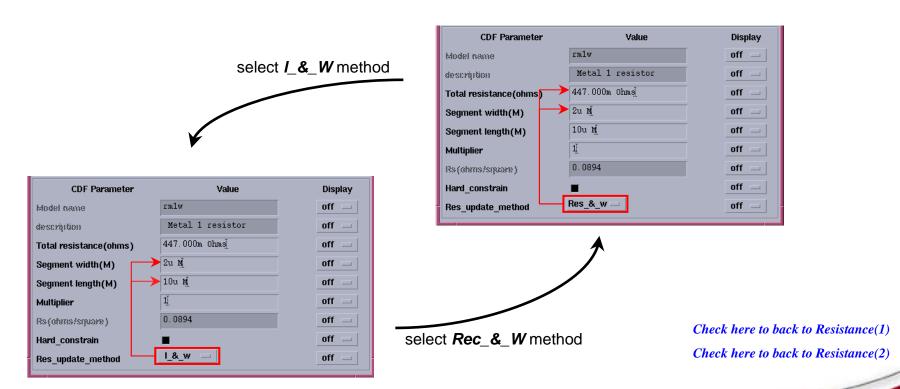
- The function of BJT_type
 - There are three dimension of pnp and npn are provided in this PDK, user can use this function to choose those device layout.



Check here to back to BJT

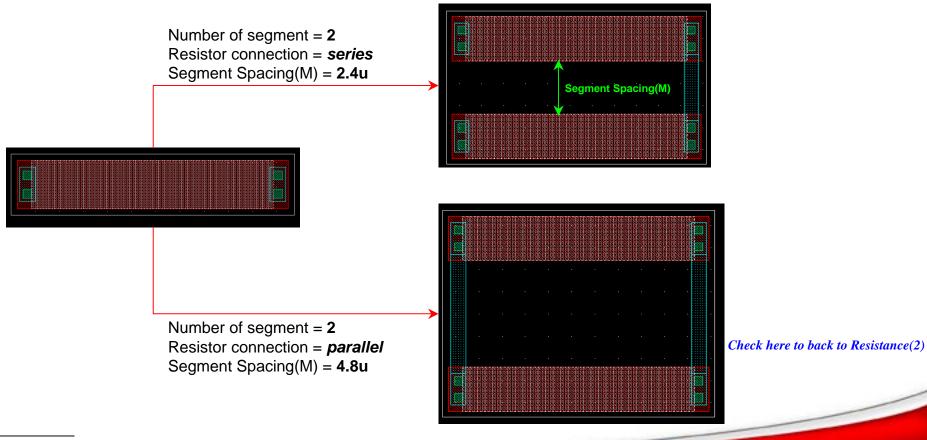


- The function of Total resistance(ohms), Segment width(M), Segment length(M) and Res_update_method
 - In the resistance cell, we provide user two kinds of input method I_&_W and Rec_&_W to modify the device resistance. When the user select I_&_W method, the input parameter will be segment length(M) and segment width(M), the other one is total resistance(ohms) and segment width(M).



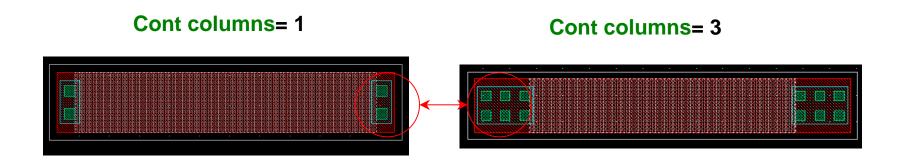


- The function of Resistor connection, Number of segment, Segment spacing(M)
 - Number of segment provide user a function to Increment the number of segment resistance, user can use Resistor connection and Segment spacing(M) to modify connection type **series** or **parallel** and segment spacing.





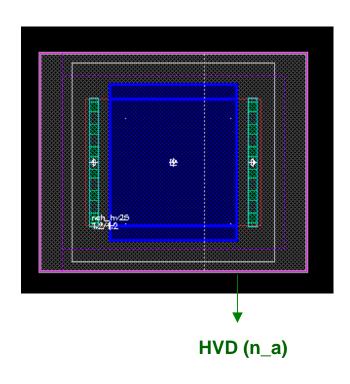
- The function of Cont columns
 - This function provide user to modify the contact columns.

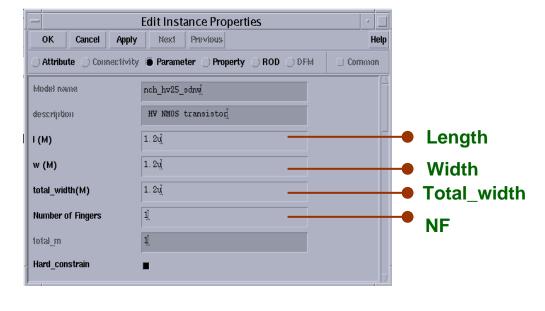


Check here to back to Resistance(2)



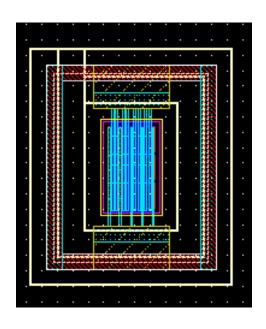
- The function of HVMOS (nch_hv25/pch_hv25)
 - This function provide user to modify the device layout

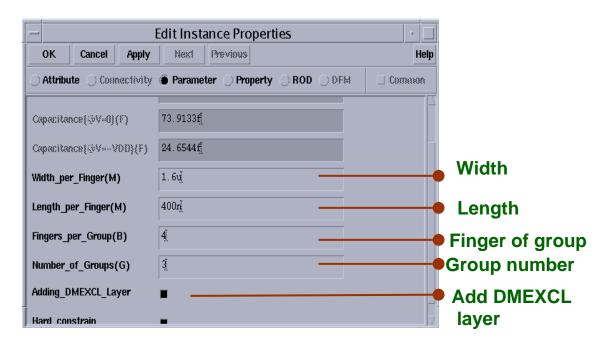






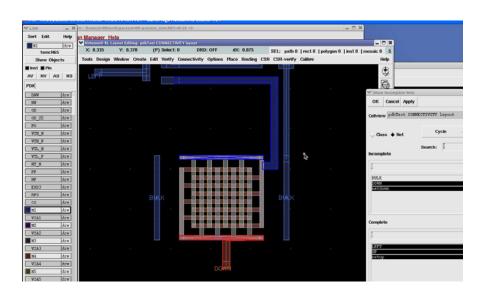
- The function of PMOSCAP_RF
 - This function provide user to modify the device layout



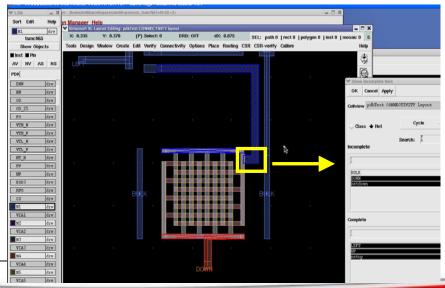




The function of CRTMOM



- No problem to add different metal layer connection flexibility.
- 2. Allow right&left side for connection but need to consider improper metal routing caused additional parasitic capacitances.



Extra Parasitic devices will be extracted in yellow mark region. Need to consider very careful.

TSMC don't recommend this kind connection.

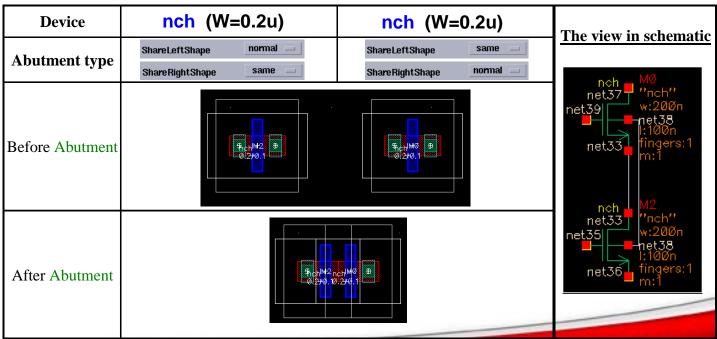


Appendix



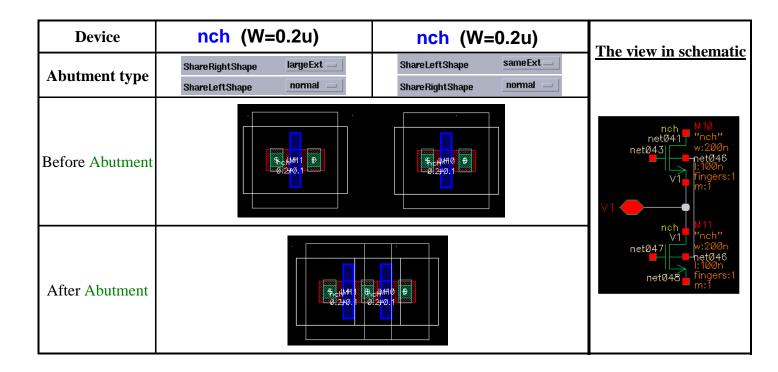
Appendix A - Abutment

- To make the user understand this function, we describe more details and examples about abutment in this section. There are two point about this function is important, first this function only support MOS device in this PDK, second there are the same type MOS (ex: nch and nch_18, pch and pch_25) can be abutted only.
- When user abut two device, the terminal B must connects certainly in the layout view so it must be connected to the same net in the schematic view.
- The system will auto determine abutment type of the both device. User can't modify abutment type.
- The same devices abut case as show in below :(Case I)



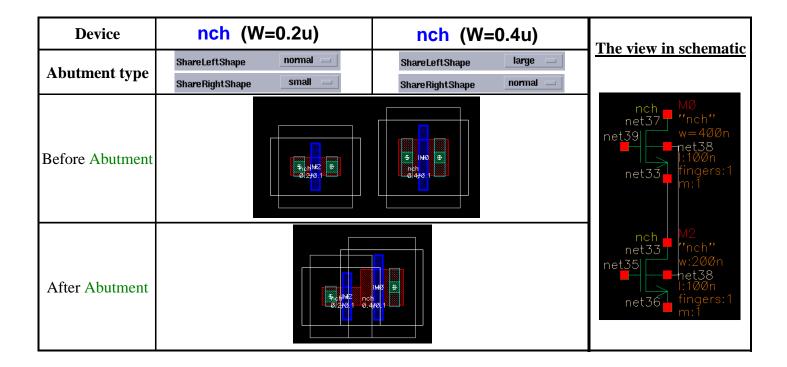


Abutment ability lets you overlap two MOS, to create a connection between two sets of shapes overlapping each other. The two sets of shapes must include pins connected to the same net. (Case II)



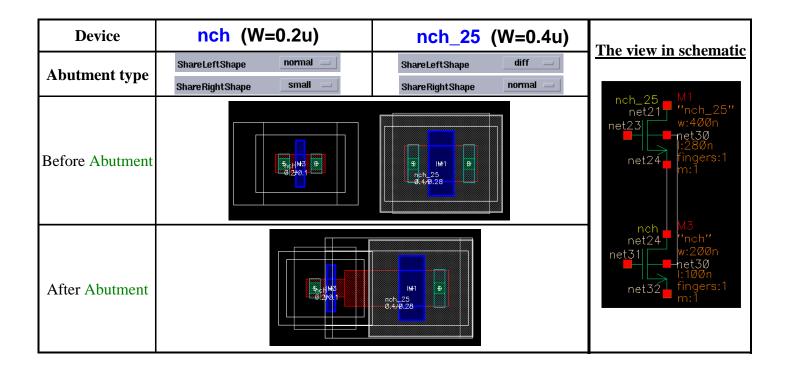


■ This case show out the different width device have been abutted. (Case III)





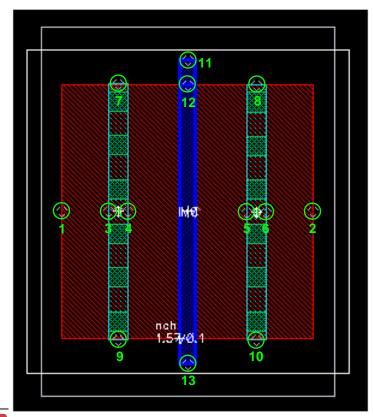
■ This case show out that the same type MOS also can be abutted. (Case IV)





Appendix B – Stretch Handles

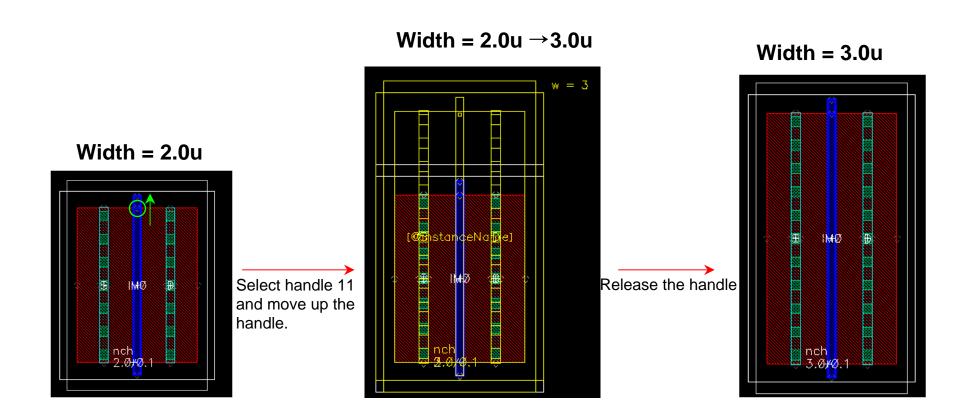
- This function lets user graphically change the value of those parameter for Pcell instances after user place them. The only one device MOS is a stretchable Pcell in this PDK.
- The system default is not show out the stretch handles, user must be enable the function manually. (Direct: in the layout view Options → Display option → Stretch Handles)



Stretch Handles number	Stretch	direction
1		\rightarrow
2	←	\rightarrow
3, 5	•	—
4, 6	_	→
7, 8		\
9, 10		↑
11		↑
13		→
12	1	\downarrow



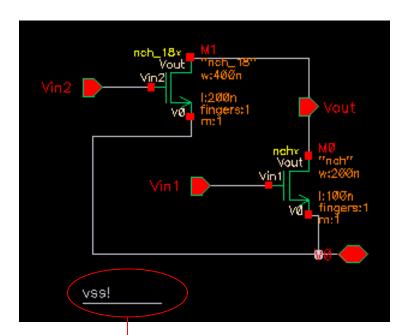
■ A example to show out the stretch case when the user stretch the handle 12.





Appendix C – The three terminal MOS substrate pin

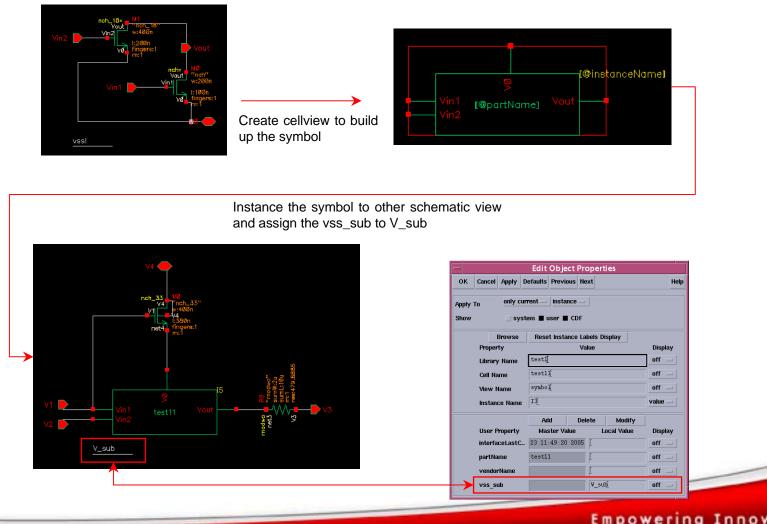
In three terminal MOS, we create a parameter for substrate pin. The pin name is vss_sub in NMOS and vdd_sub in PMOS. When user instances the three terminal MOS, all of the devices substrate terminal will connect to vss_sub or vdd_sub. User doesn't need to draw the wire to link the device. In the hierarchy structure, user can add a parameter in CDF form to assign the substrate terminal name.



When user instances the nchx and nch_18x (three terminal MOS), all of the devices substrate terminal will connect to vss_sub (VSS!)



■ In the hierarchy structure, user can add a parameter in CDF form to assign the substrate terminal name.



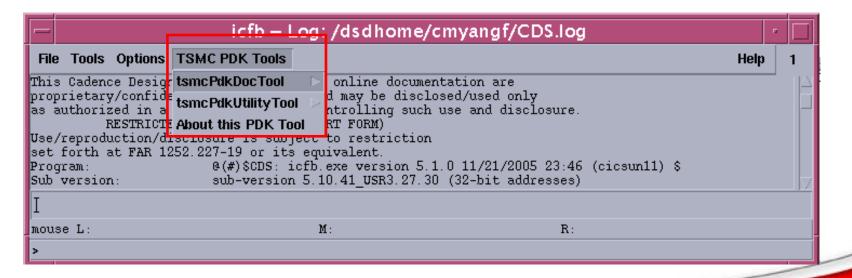


- Appendix D TSMC Utility
 - tsmcPdkDocTool
 - tsmcPdkDocumentViewer

tsmcPdkToolAbout

tsmcPdkUtilityTool

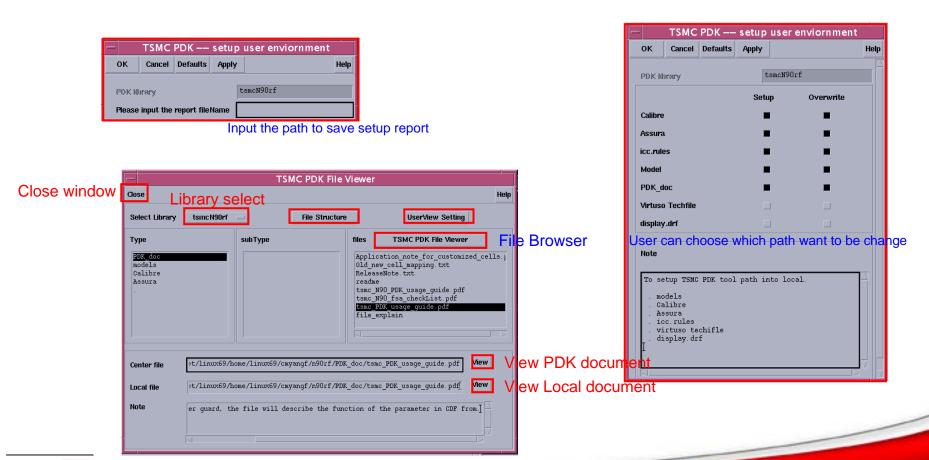
- tsmcPdkFC set
- tsmcPdkDFMset
- tsmcPdkUpdateCDF
- tsmcPdkChangeOD
- tsmcPdkZoomIn
- tsmcPdkLVL
- tsmcPdkFileViewer





tsmcPdkDocTool:

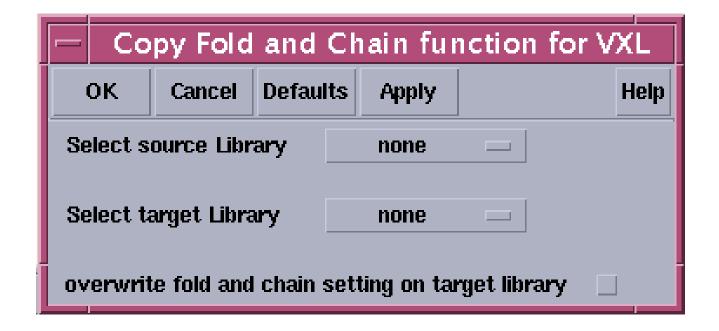
■ Sometimes TSMC PDK user will use symbolic link to use the PDK, user will encounter a problem - documents and technology file path missing. TSMC provide tsmcPdkDocumentView function to solve this problem. The function will re-connect the document directory and replace the default path setup.





tsmcPdkUtilityTool:

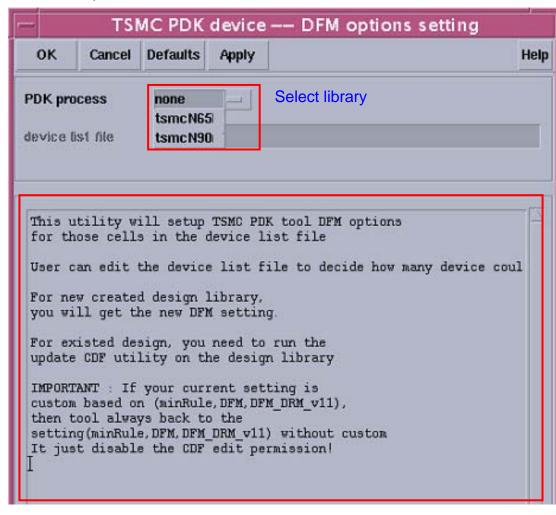
■ The function of tsmcPdkFC_set is a utility function fold and chain.





tsmcPdkUtilityTool :

The function of tsmcPdkDFMset will set the pcell to mimRule or DFM or DFM_DRMv11 or custom setup.

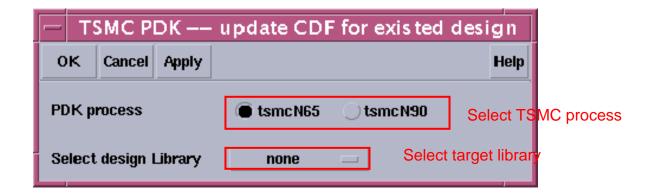


Description



tsmcPdkUtilityTool :

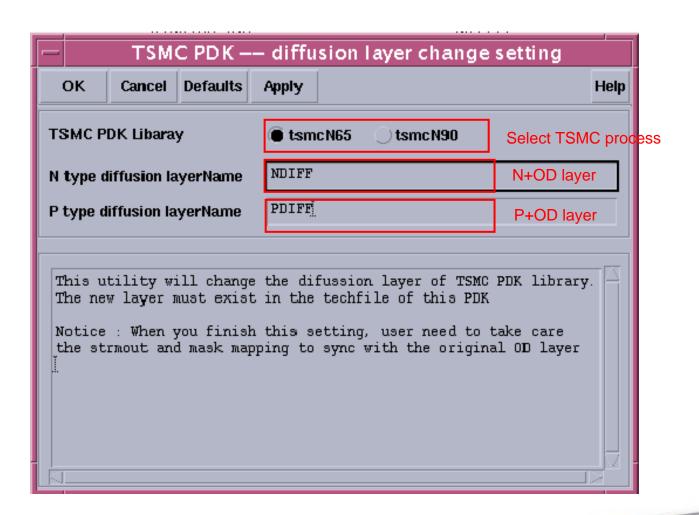
■ The function of tsmcPdkUpdateCDF will run TSMC CDF parameter update utility.





tsmcPdkUtilityTool :

■ The function of tsmcPdkChangeOD will change the N+OD and P+OD layer.





tsmcPdkUtilityTool:

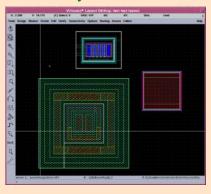
■ The function of tsmcPdkZoomIn is a utility to help user easy to find the layout.

	zoom into XY position(schematic/layout)							
ок	Cancel	Defaults	Apply					Help
Input	coordinat	es			Create bo	oundary		
cente	rX	12	Ž.		Create the	boundary		
cente	r Y	2 <u>i</u>			houndary (ayerName		
zoom	In window s	size 30)		Boundary (ayerPterpase		
								=
	visit his	tory					Reset	
	cente	rX	cente	rY	zooml	ln layer	purpose	
	12.000 15.000		000 000	30.000 15.000	ref	drawing		
Coo	dinate his	story						

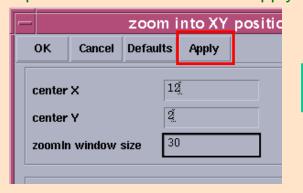


Way1

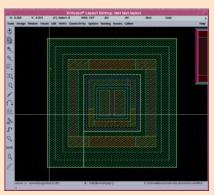
Select layout window



input coordinates and check Apply

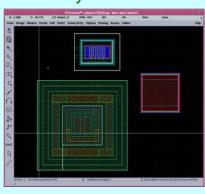


Window zoom in



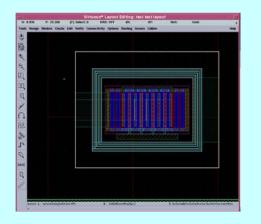
Way2

Select layout window



Double check coordinate history

visit history					Re
centerX	cen	terY	zoomin	layer	pur
12.000	2.000	30.000			
15.000	22.000	15.000	ref o	lrawing	





•tsmcPdkUtilityTool :

■ tsmcPdkLVL utility:

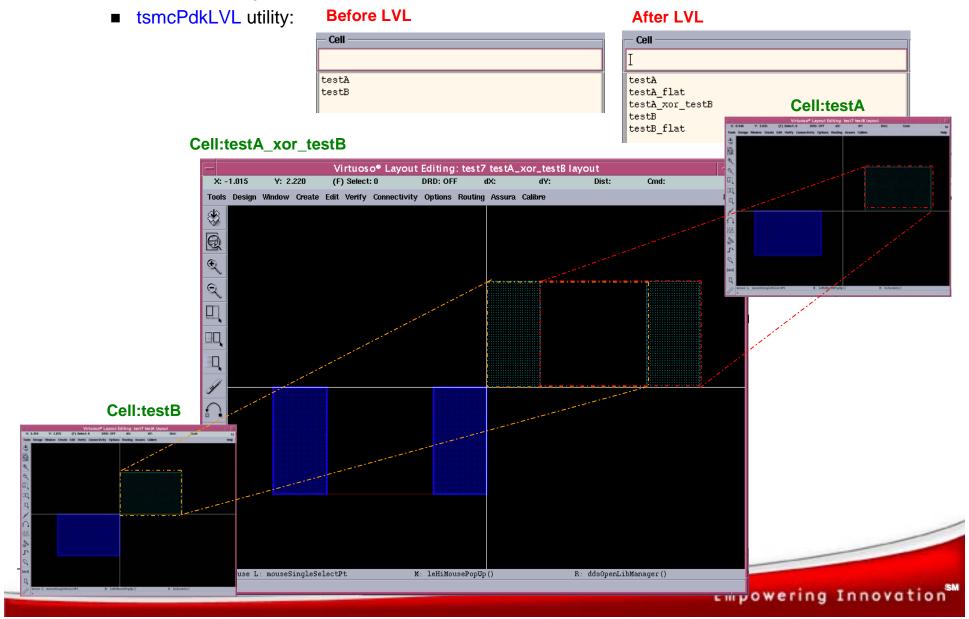
	Layout VS. Layout without layer and rule setting (LVL)	
First cell setup	Cell for 1st layout Lib/cell Browser for first layout Library for 1st layout Cell for 1st layout keep shapes form 1st layout on y1 layer	
Flatten option	Flease input the comparision report directory Please input the comparision report directory Please read following usage procedure first Selection: choose first layout and second layout(DFII format). choose the flatten setting choose the text mode output report location. Action:	Function description
	first cellName will be flatten into cellName1 flat second cellName will be flatten into cellName2 flat. the LVL comparision will be done without rule and layer setting. Limitation: cellName1 and cellName2 can't have the differece with "_flat" only Result: the reslut cellview is "cellName1_xor_cellName2" in library1. All shapes in the first layout will be created by "y1 drawing" All shapes in the second layout will be created by "y2 drawing" The differences of each layerName will be created by the same layerName Example:	y.

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TSMCN65 PDK Usage Guide



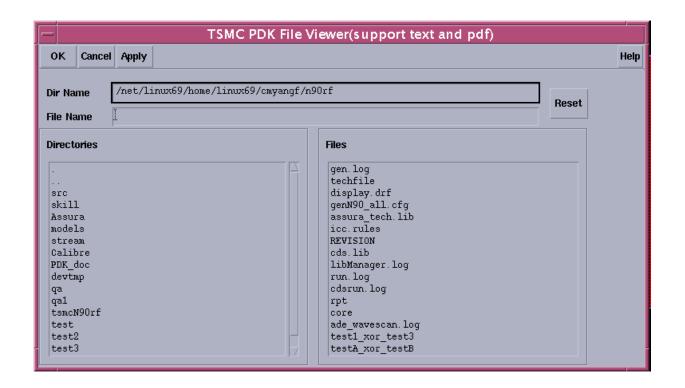
tsmcPdkUtilityTool:





•tsmcPdkUtilityTool :

■ tsmcPdkFileViewer – TSMC file browser tool, user can easily find the file they needs.





•tsmcPdkToolAbout :

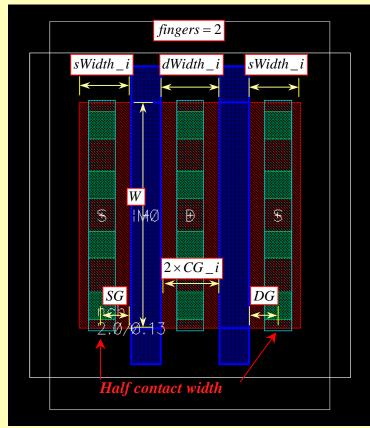




- Appendix E AS AD PS PD NRS NRD methodology
 - In this section, we will description that the PDK how to calculate as, ad, ps, pd, nrs and nrd.

Case I

• Normal MOS with multi fingers



$$S_{Area_total} = \sum_{i=1}^{n} sWidth_i \times w$$
 $AS = S_{Area_total} / fingers$

$$S_{Peri_total} = \sum_{i=1} (sWidth_i + w \times N_s) \times 2 \quad PS = S_{Peri_total} / fingers$$

$$D_{Area_total} = \sum_{i=1} dWidth_i \times w$$
 $AD = D_{Area_total} / fingers$

$$D_{Peri_total} = \sum_{i=1} (dWidth_i + w \times N_d) \times 2 \ PD = D_{Peri_total} / fingers$$

 N_s : Number of Source N_d : Number of Drain

$$NRS = \left(\sum_{i=1}^{s} CG_i - s + SG_s + DG_s\right) / fingers / w$$

$$NRD = (\sum_{i=1} CG_i - d + SG_d + DG_d) / fingers / w$$

 $CG_i d: CG_i$ in Drain diffusion area

 $CG_i_s: CG_i$ in Source diffusion area

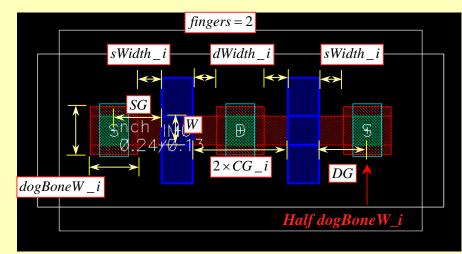
 $SG_d(SG_s) : SG$ in Drain(Source) diffusion area

 $DG_d(DG_s)$: DG in Drain(Source) diffusion area



Case II

• Dog Bone MOS with multi fingers



$$S_{Area_total} = \sum_{i=1}^{s} sWid\underline{th}_{i} \times w + dogBoneW_{i} \times dogBoneW_{i} \times N_{s}$$

$$D_{Area_total} = \sum_{i=1} dWidth_i \times w + dogBoneW_i \times dogBoneW_i \times N_d$$

$$S_{Peri_total} = \sum_{i=1} sWidth_i \times 2 + dogBoneW_i \times 4 \times N_s$$

$$D_{Peri_total} = \sum_{i=1}^{n} dWidth_i \times 2 + dogBoneW_i \times 4 \times N_d$$

 N_s : Number of Source N_d : Number of Drain

$$AS = S_{Area total} / fingers$$

$$PS = S_{Peri\ total} / fingers$$

$$AD = D_{Area_total} / fingers$$

$$PD = D_{Peri\ total} / fingers$$

$$NRS = \left(\sum_{i=1}^{s} CG_{i} - s + SG_{s} + DG_{s}\right) / fingers / w$$

$$NRD = (\sum_{i=1}^{n} CG_i - d + SG_i - d + DG_i - d) / fingers / w$$

$$CG_i_d: CG_i$$
 in Drain diffusion area

$$CG_i_s: CG_i$$
 in Source diffusion area

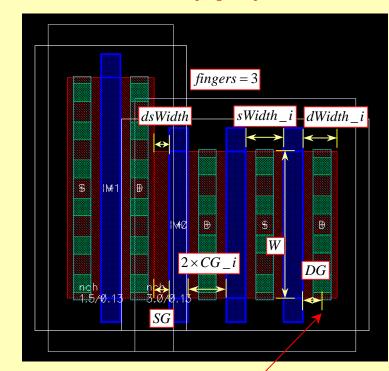
$$SG_d(SG_s): SG$$
 in Drain(Source) diffusion area

$$DG_d(DG_s)$$
: DG in Drain(Source) diffusion area



Case III

• Normal MOS with multi fingers after abut



Half contact width

$$S_{Area_total} = (\sum_{i=1} sWidth_i + dsWidth) \times w$$

$$S_{Peri_total} = (\sum_{i=1} sWidth_i + dsWidth + w \times N_s) \times 2$$

$$D_{Area_total} = (\sum_{i=1} dWidth_i + ddWidth) \times w$$

$$D_{Peri_total} = (\sum_{i=1} dWidth_i + ddWidth + w \times N_d) \times 2$$

$$N_s$$
: Number of Source N_d : Number of Drain

$$AS = S_{Area_total} / fingers$$
 $PS = S_{Peri_total} / fingers$

$$AD = D_{Area total} / fingers$$
 $PD = D_{Peri total} / fingers$

$$NRS = (\sum_{i=1}^{s} CG_i s + SG_s + DG_s) / fingers / w$$

$$NRD = (\sum_{i=1} CG_i d + SG_d + DG_d) / fingers / w$$

$$CG_i_d: CG_i$$
 in Drain diffusion area

$$CG_i s : CG_i$$
 in Source diffusion area

$$SG_d(SG_s): SG$$
 in Drain(Source) diffusion area

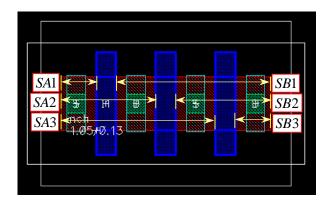
$$DG_d(DG_s)$$
: DG in Drain(Source) diffusion area



Appendix F – SA SB SD methodology

- In this section, we will description that the PDK how to calculate sa and sb.
- For post-layout simulation (netlists extracted from the layout): Treat each finger of devices as an independent MOS. And thus PDK assigns different SA/SB to each independent MOS. So the netlist will look like (if finger_number=3):

m1 d g s b w=channel width I =channel length SA=SA1 SB=SB1 m2 d g s b w=channel width I =channel length SA=SA2 SB=SB2 m3 d g s b w=channel width I =channel length SA=SA3 SB=SB3



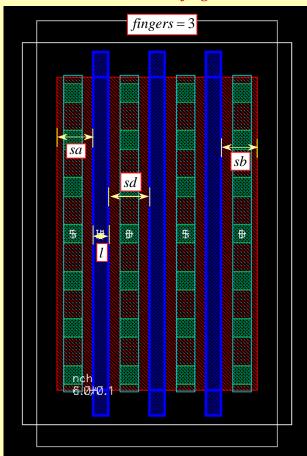
For pre-layout simultation (netlists estimated from schematic diagram):
PDK sets m=finger_number, SA=SA, SB=SB and SD=SD. So the netlist will look like
m0 d g s b w=channel width I =channel length m=1 SA=SA SB=SB SD=SD
Please refer next two page to understand the SA, SB and SD in layout



■ In this page, we will description that the PDK how to calculate SA, SB and SD.

Case I

• Normal MOS with multi fingers



SA = sa: In the netlist, SA equal to sa

SB = sb: In the netlist, SB equal to sb

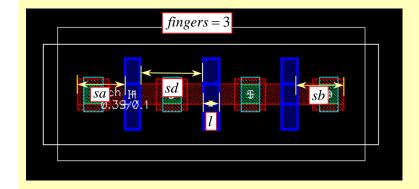
SB = sd: In the netlist, SB equal to sd



■ In this page, we will description that the PDK how to calculate SA, SB and SD.

Case II

• Dog Bone MOS with multi fingers



SA = sa: In the netlist, SA equal to sa

SB = sb: In the netlist, SB equal to sb

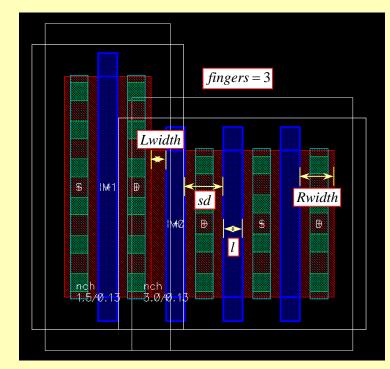
SB = sd: In the netlist, SB equal to sd



■ In this page, we will description that the PDK how to calculate SAeff and SBeff.

Case III

• Normal MOS with multi fingers after abut



$$Sum1_i = 1/(Lwidth + i \times (sd + l) + 0.5 \times l)$$

$$SAeff = fingers / \sum_{i=0}^{fingers-1} Sum1_i - 0.5 \times l$$

$$Sum2_i = 1/(Rwidth + i \times (sd + l) + 0.5 \times l)$$

$$SBeff = fingers / \sum_{i=0}^{fingers-1} Sum 2_i - 0.5 \times l$$

$$SAeff = SAeff$$

$$SBeff = SBeff$$

SA = SAeff: In the netlist, SA equal to SAeff

SB = SBeff: In the netlist, SB equal to SBeff

SA = sa: In the netlist, SA equal to sa

SB = sb: In the netlist, SB equal to sb

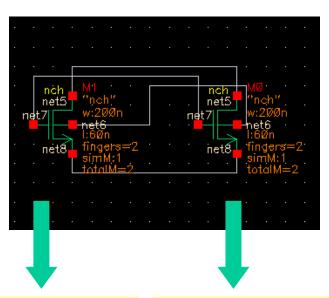
SB = sd: In the netlist, SB equal to sd



Appendix G – Multiple devices Abutment methodology

In this section, we will describe that the PDK how to use multiple devices abutment

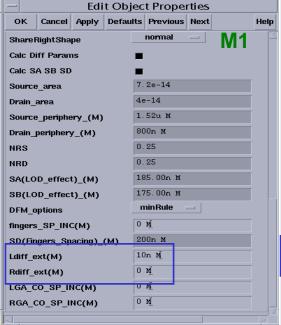
with Ldiff_ext and Rdiff_ext

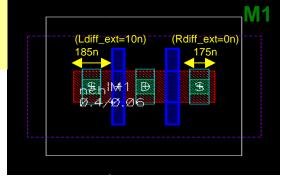


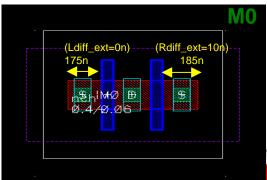
M1: Ldiff_ext(M):10n Ldiff_ext(M): 0n Rdiff_ext(M): 0n

MO:

Rdiff_ext(M):10n







Edit Object Properties

7.2e-14

4e-14

1.52u M

800n M

0.25

0.25

0 M,

0 M<u>ř</u>

0 M

10n M

200n M

175.00n M

185.00n M

minRule

Cancel Apply Defaults Previous Next

Source area

Drain area

Source_periphery_(M)

Drain_periphery_(M)

SA(LOD_effect)_(M)

SB(LOD_effect)_(M)

fingers_SP_INC(M)

LGA CO SP INC(M)

RGA CO SP INC(M)

SD(Fingers_Spacing)_(M)

DFM_options

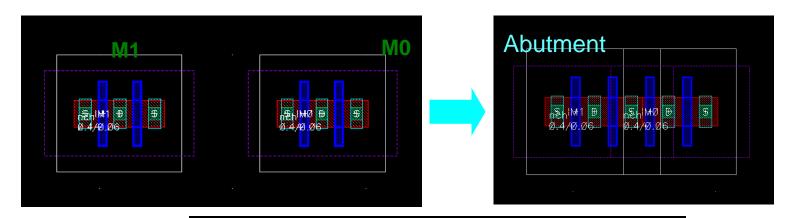
Ldiff ext(M)

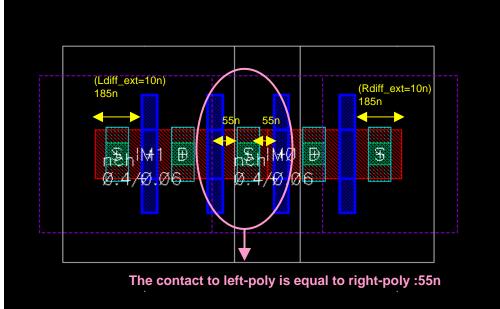
Rdiff ext(M)





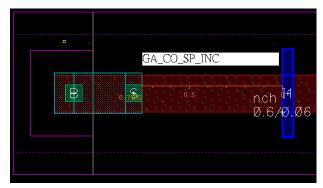
■use multiple devices abutment with Ldiff_ext and Rdiff_ext







- Appendix H MOS pcell usage GA_CO_SP_INC
- Function introduction
 - GA_CO_SP_INC : Add gate to contact spacing for DFM
 - Real spacing = GA_CO_SP_INC + Original spacing



- Ldiff_ext : extend left-hand side OD
- Rdiff_ext : extend right-hand side OD



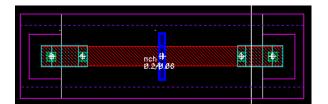
- Appendix H MOS pcell usage GA_CO_SP_INC
- Problem description
 - Mos pcell
 - When turning on bodytie as integred and set GA_CO_SP_INC to 700n, mos pcell will fail.



bodytie_typeL	Integred =
left_bulkFlush	
bodytie_typeR	Integred =
right_bulkFlush	
DFM_options	custom =
Upper_PO_EX_INC(M)	O <u>ř.</u>
Lower_PO_EX_INC(M)	0 <u>ř</u>
GA_GA_SP_INC(M)	O <u>ř</u>
GA_CO_SP_INC(M)	700r <u>i</u>



- Appendix H MOS pcell usage GA_CO_SP_INC
- Problem solution
 - Correct usage method :
 - Before setting GA_CO_SP_INC, Ldiff and Rdiff should extend first.
 - Let contacts have space to insert or contact will over-extend.



bodytie_typeL	Integred =	
left_bulkFlush		
bodytie_typeR	Integred =	
right_bulkFlush		
DFM_options	custom =	
Upper_PO_EX_INC(M)	O <u>Ľ</u>	
Lower_PO_EX_INC(M)	<u>ď</u>	
GA_GA_SP_INC(M)	OĽ	
GA_CO_SP_INC(M)	700r <u>š</u>	
_diff_ext(M)	700 <u>ri</u>	
Rdiff_ext(M)	700r <u>i</u>	



- Appendix H Sdshrink and Poly Gate position
 - Routing method: M1 will extend if route_source_drain option set to "both".

